

Stacey Francine Bent

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Education

1992	Ph.D., Chemistry	Stanford University Advisor: Richard Zare
1987	B.S., Chemical Engineering	University of California, Berkeley Summa cum laude

Professional and Academic Appointments

2022 – present	Professor of Energy Science and Engineering, Stanford University
2019 – 2025	Vice Provost for Graduate Education and Postdoctoral Affairs, Stanford University
2016 – 2019	Senior Associate Dean for Faculty and Academic Affairs, School of Engineering, Stanford University
2015 – 2016	Department Chair, Chemical Engineering, Stanford University
2023 – present	Bass University Fellow in Undergraduate Education
2013 – 2023	Bert and Candace Forbes University Fellow in Undergraduate Education
2012 – present	Jagdeep and Roshni Singh Professor in the School of Engineering
2005 – present	Professor of Chemical Engineering, Stanford University
2005 – present	Professor of Chemistry, by courtesy, Stanford University
2005 – present	Professor of Materials Science and Engineering, by courtesy, Stanford University
2005 – present	Professor of Electrical Engineering, by courtesy, Stanford University
2010 – 2019	Director, TomKat Center for Sustainable Energy
2009 – present	Senior Fellow, Precourt Institute for Energy
2009 – 2015	Co-Director, Center on Nanostructuring for Efficient Energy Conversion (CNEEC), a DOE Energy Frontier Research Center
2006	Sabbatical Visitor, Physics Dept, Chalmers University, Gothenburg, Sweden
2005 – 2006	Associate Chair, Department of Chemical Engineering, Stanford University
2005 – 2007	Associate Professor, by courtesy, of Ophthalmology, Stanford University
2002 – 2005	Associate Professor of Chemical Engineering, Stanford University
1998 – 2002	Assistant Professor of Chemical Engineering, Stanford University, CA
1994 – 1998	Assistant Professor of Chemistry, New York University
1992 – 1993	Postdoctoral Research Associate, AT&T Bell Laboratories, Murray Hill, NJ
1987, 1989	Fellowship research at AT&T Bell Laboratories, Murray Hill, NJ
1987 – 1992	Graduate Research, Stanford University with Prof. Richard N. Zare
1984 – 1987	Undergraduate Research Assistant, UC, Berkeley, CA with Prof. Y. T. Lee

Awards and Honors

2025	Dourdeville Memorial Lectureship on Engineering in Service to Society, Brown University
2022	Stanford-Samsung Research Initiative Faculty Award

2021	Braskem Award for Excellence in Materials Engineering and Science (AIChE)
2021	ALD (Atomic Layer Deposition) 2021 Innovator Award
2021	Dorn Lecturer, Northwestern University
2020	SRC Technical Excellence Award
2020	National Academy of Engineering
2020/2021	Racheff Award Lecturer, University of Illinois
2018	ACS Award in Surface Chemistry
2017	Morino Lecturer, Japan
2016	Reilly Lectureship, University of Notre Dame
2013	Bert and Candace Forbes University Fellow in Undergraduate Education
2013	Fellow of the American Chemical Society (ACS)
2013	Stanford Medal for Faculty Excellence Fostering Undergraduate Research
2012	Jagdeep and Roshni Singh Endowed Professorship
2011	Fellow of the World Technology Network
2006	Fellow of the AVS
2006	Tau Beta Pi Award for Excellence in Undergraduate Teaching
2004	H. Willard Davis Lecturer, University of South Carolina
2001	Coblentz Award for Molecular Spectroscopy, Coblentz Society
2000	Peter Mark Memorial Award of the American Vacuum Society
1998-2001	Frederick E. Terman Faculty Fellow, Stanford University
1998-2003	Camille Dreyfus Teacher-Scholar Award
1998	Research Corporation Cottrell Scholar
1997-2000	Beckman Young Investigator Award
1995-2000	National Science Foundation CAREER Award
1990-1991	Evelyn McBain Graduate Fellowship
1987-1990	National Science Foundation Predoctoral Fellowship
1987-1992	AT&T Graduate Research Program for Women, Grant
1987	Phi Beta Kappa
1987	University Certificate of Distinction
1987	The Departmental Citation in Chemical Engineering
1987	E.O. Saegebarth Prize for Promise in Chemistry

Teaching Activities

Stanford University:

Kinetics and Reactor Design, ChE 170 (UG)

Chemical Engineering Laboratory, ChE 185A (UG)

Applied Spectroscopy, ChE 345 (Grad)

Microelectronics Processing Technology, ChE 140 (UG)

Structure and Reactivity of Solid Surfaces, ChE 442/424 (Grad)

How Computer Chips Are Made (Sophomore College UG course)

Energy Technologies for a Sustainable Future (Sophomore College UG course)

Energy: Chemical Transformations for Production, Storage and Use, ChE 25E (UG)

New York University:

Physical Chemistry II (Quantum Mechanics / Spectroscopy) (UG)

Experimental Methods Laboratory (UG)

Energy and the Environment (UG)

Professional Activities

2025 – present	National Academy of Engineering, Chair of Section 3 Chemical Engineering
2025 – present	Editorial Advisory Board member, <i>Current Opinion in Solid State and Materials Science</i>
2025 – present	External Review Team, Department of Chemical and Biological Engineering, Northwestern University
2024 – 2025	Member of the National Academies Committee for Quadrennial Review of the National Nanotechnology Initiative
2024 – present	National Academy of Engineering, Section 3 Search Committee, Materials subteam
2023 – present	Editorial Board member, <i>ACS Materials Letters</i>
2022 – present	Co-chair, Telluride Science Research Center Workshop on Semiconductor Surface Chemistry (July 27-31, 2026)
2023 – present	Member, MIT Undergraduate and Graduate Education Visiting Committee
2022 – 2024	AIChE Awards Selection Subcommittee
2022 – 2024	AIChE Materials Engineering and Sciences Division (MESD) Awards Committee
2021 – 2025	Department of Energy Basic Energy Sciences Advisory Committee (BESAC)
2021 – 2023	Scientific Advisory Board Member, Pivotal Systems
2021 – 2024	National Academy of Engineering, Section 3 Peer Committee
2021	Review panel, Villum Foundation, Denmark
2021 – present	Editorial Board member, <i>Journal of Vacuum Science and Technology</i>
2021	Conference Co-Chair, Area Selective ALD (ASD) 2021 Conference
2020	Conference Chair, Area Selective ALD (ASD) 2020 Conference (cancelled)
2019	External peer review, CIFAR Bio-inspired Solar Energy Program, Toronto
2018 – present	Visiting Committee, Department of Chemical Engineering, MIT
2018 – 2022	Scientific Committee, EuroCVD-Baltic ALD 2019 and 2022 conferences
2018 – 2019	Co-organizer, 2019 Fall Materials Research Society (MRS) Meeting, symposium on Advanced atomic layer deposition and chemical vapour deposition techniques and applications
2017 – present	Advisory Committee member, Atomic Layer Deposition (ALD) Conference
2017 – 2018	Program Committee member, Area Selective ALD (ASD) 2018 Conference
2017 – present	Editorial Advisory Board member, <i>Langmuir</i>
2016 – 2020	External Advisory Board, UCSB Chemical Engineering Department
2016 – present	Editorial Advisory Board member, <i>Surface Science</i>
2015 – 2019	Member of the International Advisory Board, MAPEX Center for Materials and Processes, University of Bremen, Germany
2015 – 2018	Member of the Scientific Advisory Board, French Technological Research Institute (IRT) Saint Exupery for aeronautics, space and embedded systems
2014 – 2016	Associate Editor, <i>Chemistry of Materials</i>

2014 – 2015	Program Committee, Energy Frontiers Focus Topical Session for 62nd AVS Meeting, 2015
2013 – 2014	Editor, Surface Science Reports
2013	Visiting Committee, Department of Chemical and Biomolecular Engineering, UCLA
2013 – 2014	Organizing Committee, Symposium on Selective Deposition and Etch for AVS 61 st Annual International Conference, 2014
2012 – 2017	Chair and Vice Chair of the Energy Subdivision of the Physical Chemistry Division, American Chemical Society
2012 – 2013	Organizing Committee, International Workshop on Nanotechnology for Next Generation High Efficiency Photovoltaics
2011 – 2012	Member of the ACS Presidential Commission on Graduate Education in the Chemical Sciences, American Chemical Society
2011 – 2013	Director, Materials Engineering and Sciences Division, American Institute of Chemical Engineering (AIChE)
2010 – 2019	Director, TomKat Center for Sustainable Energy
2009 – 2015	Co-Director, Center on Nanostructuring for Efficient Energy Conversion (CNEEC)
2009 – present	Senior Fellow, Precourt Institute for Energy
2009 – present	Affiliated Faculty Member, Woods Institute for the Environment
2008 – 2014	Editorial Board Member, <i>Annual Review of Chemical and Biomolecular Engineering</i>
2004 – 2014	Member of ACS Executive Director's 2020 Committee
2010	Co-Chair, Workshop on Grid Integration of Renewable Energy
2010	Chair of the Trustees, AVS
2009	Chair, Gordon Research Conference on Chemical Reactions at Surfaces
2008	International Advisory Committee, 25 th European Conference on Surface Science (ECOSS), Liverpool, UK
2007 – 2010	Trustee of the AVS (American Vacuum Society)
2007	Vice-Chair, Gordon Research Conference on Chemical Reactions at Surfaces
2007 – 2009	International Advisory and Programme Committee, International Conference on the Formation of Semiconductor Interfaces (ICFSI)
2007	International Advising Committee, Fourth San Luis Conference on Surfaces, Interfaces and Catalysis, Cuernavaca, Mexico
2006 – 2012	Symposium Organizer, Electrochemical Society Symposium on Atomic Layer Deposition Applications
2004	International Organizing Committee, International Conference on Cat-CVD Process, Denver Colorado 2002, The Netherlands
2004	Member, Local Organizing Committee, Physical Electronics Conference, Davis, CA
2004	Co-organizer, Symposium on Nanoscience and Bionanoscience, Sponsored by the Northern California Chapter of the AVS, Stanford, CA
2004	Co-organizer, INMP Workshop on Mobility and Interface Issues in High k Dielectrics
2002–2003	Division Chair, Surface Science Division, American Vacuum Society (AVS)
2001–2006	Advisory Editorial Board member, <i>Surface Science</i>

2001–2002	Program Chair, American Vacuum Society (AVS) Surface Science Division
2001	Program Committee Member, International Vacuum Congress (IVC)-15 Symposium, San Francisco
2001	Session Organizer and Chair, "Reaction Kinetics in Electronic Materials Processes," Annual Meeting of the American Institute of Chemical Engineers, Reno
2000–2006	Continuing Symposium Chair, "Molecular Processes at Solid Surfaces," American Chemical Society, Division of Colloid and Surface Chemistry
2000	Session Organizer and Chair, "Semiconductor Surface Chemistry," Annual Meeting of the American Institute of Chemical Engineers, Los Angeles
1998–2003	Member of the Executive Committee, Surface Science Division of the American Vacuum Society
Ongoing	External reviewer for the National Science Foundation, Research Corporation, Petroleum Research Fund, Beckman Foundation, Department of Energy, Air Force Office of Scientific Research, Journal of the American Chemical Society, Journal of Chemical Physics, Journal of Physical Chemistry, Journal of Vacuum Science and Technology, Langmuir, Surface Science, Journal of Applied Physics, Applied Physics Letters, Chemistry of Materials, Journal of Materials Chemistry, Journal of Crystal Growth, Chemical Communications, Advanced Materials, Advanced Functional Materials, Advanced Energy Materials, Catalysis Letters, Energy and Environmental Science, Thin Solid Films, Chemical Reviews, Nature Nanotechnology, Nature Chemistry, Nature Materials, Nano Letters, Angewandte Chemie, ACS Catalysis, ACS Nano, ACS Applied Materials and Interfaces, Science

University and Departmental Service

2023– 2024	Chemical Engineering Department Colloquium Organizing Committee
2022– 2024	Graduate Degree-Programs Committee, Department of Energy Science and Engineering
2022– 2023	Faculty Search Committee, Department of Chemical Engineering
2021– 2023	Undergraduate Committee, Department of Chemical Engineering
2020 – 2023	Steering Committee for Western Association of Schools and Colleges (WASC) accreditation
2020 – 2022	COVID-19 Academic Policy Group, Research Recovery Co-Chair
2020 – 2021	Chemical Engineering Department Committee on Diversity, Equity and Inclusion (DEI)
2020	Interviewer for Knight-Hennessy Scholars program
2019 – 2025	Advisory Committee of Institutional Research & Decision Support (IR&DS)
2018 – 2019	Co-Chair of the Nano Facilities Design Team
2018 – 2023	Stanford University Budget Group
2018 – 2019	Faculty Survey Advisory Committee
2017 – 2018	Committee on Academic Roles and Responsibilities, School of Medicine
2017 – 2018	Co-Chair of the Academic Steering Group (ASG) on Education for University Long Range Planning
2016 - 2017	Faculty Senate Steering Committee

2016 - 2018	Stanford University Faculty Senate
2015 – 2019	School of Engineering Executive Committee
2015	Member of the Undergraduate Research Advisory Panel (URAP), Office of the Vice Provost for Undergraduate Education (VPUE)
2015	Mentor, Leland Scholars summer bridge program (LSP)
2014 – 2025	Faculty Resource Advisor, Diversifying Academia, Recruiting Excellence (DARE) program
2013 – 2014	Search Committee for Dean of the School of Engineering
2013 – 2014	Associate Lab Director (ALD) Search Committee, SLAC
2011 – 2019	Advisory Board, Stanford Energy Club
2011 – 2016	Chair, Undergraduate Curriculum Committee, Dept of Chemical Engineering
2010 – 2016	Steering Committee, Connecting the Dots Program
2003 – 2019	Faculty Committee, Global Climate and Energy Program (GCEP)
2011 – 2012	Faculty Search Committee, Department of Chemical Engineering
2010 – 2011	Faculty Search Committee, Precourt Institute for Energy (PIE)
2009 – 2010	Stanford University Committee on Committees
2009	Planning Committee, Uncommon Dialogue on Large Scale Solar Systems
2009 – 2011	Safety Representative for Stauffer III Building, Department of Chemical Engineering
2008 – 2011	Chair, Graduate Admission Committee, Department of Chemical Engineering
2008 – 2009	Faculty Search Committee, Department of Bioengineering
2007 – 2011	Stanford University Faculty Senate
2007 – 2008	Faculty Search Committee, Department of Materials Science and Engineering
2006 – 2007	Departmental Colloquium Committee, Chair
2006 – 2007	Faculty Search Committee, Departments of Electrical Engineering and Bioengineering
2006	Energy Science and Technology Strategic Planning Committee, School of Engineering
2005 – 2006	SEQ2 Building Committee Member
2005 – 2006	Graduate Curriculum Review Committee, Department of Chemical Engineering
2004 – 2005	Chair, Faculty Search Committee, Department of Chemical Engineering
2004 – 2005	Faculty Search Committee, Department of Mechanical Engineering
2004 – 2005	Commission on Graduate Education
2003 – 2004	1 st Year Ph.D. Advisor, Department of Chemical Engineering
2002 – 2006	Subcommittee on Academic Standards
2002 – 2003	Chair, Faculty Search Committee, Department of Chemical Engineering
2001 – 2004	Chemical Engineering Department ABET Committee
2001 – 2004	Safety Representative, Department of Chemical Engineering
2001 – 2004	Graduate Student Action Committee, Dept of Chemical Engineering
2000 – 2003	Undergraduate Curriculum Committee, Department of Chemical Engineering
2000 – 2001	Faculty Advisory Committee for X-Ray Photoelectron Spectrometer (XPS)

2000 – 2001	Faculty Search Committee, Department of Chemical Engineering
1998 – 1999	Graduate Curriculum Committee, Department of Chemical Engineering

Doctoral Students Supervised

1. Maynard Kong Moreno (PhD 1998) Thesis Title: Studies of the Adsorption and Reactivity of a Series of Hydrocarbons on Si(100); Present Position: Professor, Catholic University of Peru, Lima, Peru.
2. Moon-Sook Lee (PhD 1999) Thesis Title: Chemical Reactivity in the Growth and Processing of Hydrogenated SiC Materials by Chemical Vapor Deposition; Present Position: Principle Engineer, Samsung Electronics R&D Center, Korea.
3. George T. Wang (PhD 2002) Thesis Title: Reactivity of Group IV (100) Semiconductor Surfaces towards Organic Compounds; Present Position: Principle Member of Technical Staff, Sandia National Laboratories, Albuquerque, NM.
4. Collin Mui (PhD 2002) Thesis Title: Growth and Functionalization of Electronic Materials; Present Position: Staff System Engineer, Bio-Techne.
5. HaiLan Duan (PhD 2003) Thesis Title: Study of Hot Wire Chemical Vapor Deposition of Amorphous Hydrogenated Silicon Using Optical Diagnostics; Present Position: BEI Technologies, Automotive Division.
6. Gillian Zaharias (PhD 2005) Thesis Title: Hot Wire Chemical Vapor Deposition of Inorganic and Organic Thin Films for Solar Cells; Present Position: Staff Center, Ecology Center.
7. Christina Lee (PhD 2005) Thesis Title: Engineering Human Tissue for Control of Cellular Adhesion and Function for an Eventual Retinal Implant; Present Position: Manager, Manufacturing Sciences, Thermo Fisher Scientific.
8. Michael Filler (PhD 2005) Thesis Title: Organic Functionalization of the Ge(100)-2x1 Semiconductor Interface: Reaction Chemistry, Selective Attachment Strategies, and Molecular Layer Deposition; Present Position: Associate Professor, Georgia Institute of Technology.
9. Junsic Hong (PhD 2005) Thesis Title: Vapor Phase Deposition of Self-Assembled Monolayers as a Resist Towards Area-Selective Atomic Layer Deposition; Present Position: Engineer, IBM.
10. Rong Chen (PhD 2006) Thesis Title: Surface Modification for Area Selective Atomic Layer Deposition on Silicon and Germanium; Present Position: Professor, Huazhong University of Science and Technology.
11. Andre Marcus Worsley (PhD 2006) Thesis Title: Study of Key Integration Challenges for Low- κ Materials in Integrated Circuit (IC) Fabrication; Present Position: Staff Scientist, Lawrence Livermore National Laboratory.
12. Neville Mehenti (PhD 2007) Thesis Title: Novel Interfaces for Biomimetic Retinal Prostheses; Present Position: Senior Director, Gilead Sciences.
13. Xirong Jiang (PhD 2009) Thesis Title: Study of Catalysis for Solid Oxide Fuel Cells and Direct Methanol Fuel Cells; Present Position: General Manager, Tencent.
14. Paul Loscutoff (PhD 2010) Thesis Title: Growth of Organic Films on Semiconductor Surfaces: Fundamental Reactivity Studies and Molecular Layer Deposition Involving Isocyanates and Isothiocyanates; Present Position: R&D Engineer, SunPower.

15. Jessica Kachian (PhD 2010) Thesis Title: Passivation, Periodic Trends, and Selective Attachment in Organic Functionalization of Ge(100)-2x1; Present Position: Senior MTS, Intel.
16. Pendar Ardalan (PhD 2010) Thesis Title: Organic and Inorganic Surface Modification of Semiconductors for Electronic and Energy Conversion Devices; Present Position: Senior Senior Staff Technical Lead, Lam Research.
17. Jonathan Bakke (PhD 2011) Thesis Title: Atomic Layer Deposition of Materials for Applications to Photovoltaics; Present Position: Director of Global Product Management, ASM.
18. Marja Mullings (PhD 2013) Thesis Title: Exploring Spatial and Compositional Control of Conductive Materials in Atomic Layer Deposition; Present Position: Senior Sustainability and Quality Engineer, 3M.
19. Thomas Brennan (PhD 2013) Thesis Title: Interface Engineering and Characterization in Dye- and Quantum Dot-Sensitized Solar Cells; Present Position: Associate Partner, McKinsey & Company.
20. Rungthiwa Methaapanon (PhD 2013) Thesis Title: Mechanistic Studies of Titanium Dioxide and Ruthenium Atomic Layer Deposition by In Situ Techniques; Present Position: Assistant Professor, Chulalongkorn University, Thailand.
21. Han Zhou (PhD 2013) Thesis Title: Molecular Layer Deposition of Polymeric Thin Films for Applications in Semiconductor Fabrication; Present Position: Partner, Boston Consulting Group, Shanghai, China.
22. Keith Wong (PhD 2013) Thesis Title: Organic Functionalization of Ge(100)-2x1: Periodic Trends, Dative Bonding, New Functional Groups, and Multifunctional Molecules; Present Position: Modern Electron.
23. Artit Wangperawong (PhD 2014) Thesis Title: Study of New Materials, Device Structures, and Characterization Techniques for Photovoltaics; Present Position: Distinguished Engineering in AI, U.S. Bank.
24. Bonggeun Shong (PhD 2014) Thesis Title: Lateral Interactions in Organic Functionalization of Semiconductor Surfaces; Present Position: Assistant Professor, Hongik University, Korea.
25. Katie Pickrahn (PhD 2015) Thesis Title: Atomic Layer Deposition of Earth Abundant Electrocatalysts for the Oxygen Evolution Reaction; Present Position: None.
26. Steven Herron (PhD 2015) Thesis Title: Solution Deposition of Semiconductor Thin Films for Photovoltaics; Present Position: Senior Scientist, Invicta Medical.
27. Katie Roelofs (PhD 2015) Thesis Title: Interface Engineering in Inorganic-Absorber Nanostructured Solar Cells; Present Position: Senior Systems Architect, Luminous Computing.
28. Fatemeh Hashemi (PhD 2016) Thesis Topic: Area Selective Atomic Layer Deposition of Metal Oxides on Metal-Dielectric Patterns; Present Position: Research Scientist Solar Energy, TNO, Netherlands
29. Yesheng Yee (PhD 2016) Thesis Title: The Role of Crystallographic Defects in Semiconductors for Optoelectronic Applications; (jointly advised with Clemens); Present Position: KLM, Singapore

30. Nuoya Yang (PhD 2017) Thesis Title: Effects of Surface Structure, Promoters and Supports in Rhodium Catalysts for Higher Oxygenates Synthesis from Syngas; Present Position: Lam Research.
31. Axel Palmstrom (PhD 2017) Thesis Title: Next Generation Thin Film Photovoltaics: Study and Application of Surface Modification and Atomic Layer Deposition; Present Position: Staff Scientist at NREL
32. Tania Sandoval (PhD 2018) Thesis Title: Adsorption of Multifunctional Molecules on the Ge(100)-2x1 Surface; Present Position: Professor, Federico Santa Maria Technical University, Chile
33. David Bergsman (PhD 2018) Thesis Title: Molecular layer deposition: Fundamental mechanisms and applications of ultrathin organic films; Present Position: Assistant Professor, University of Washington, Seattle
34. Joseph Singh (PhD 2018) Thesis Title: Nanomaterial design via ALD: New methods and applications; Present Position: Data Scientist, Google
35. Callisto MacIsaac (PhD 2018) Thesis Title: Atomic layer deposition (ALD): Mechanisms and hybrid materials for energy applications; Present Position: Facilities Analytical Chemist, Intel, Ireland
36. Richard Closser (PhD 2019) Thesis Title: New chemistries and applications of molecular layer deposition; Present Position: Agilent
37. Jon Baker (PhD 2020) Thesis Title: Atomic Layer Deposition of Multi-Component Catalyst Systems for the Oxygen Evolution Reaction; Present Position: Lam Research
38. Dara Bobb-Semple (PhD 2020) Thesis Title: Understanding Inhibitor-Based Area Selective Atomic Layer Deposition for Dielectric-on-Dielectric Growth; Present Position: Lam Research
39. Arun Asundi (PhD 2021) Thesis Title: Understanding catalyst structure-performance relationships through precise synthesis and in situ characterization; Present Position: Postdoctoral fellow at Stanford Synchrotron Radiation Lightsource (SSRL)
40. Camila de Paula Teixeira (PhD 2021) Thesis Title: Mechanistic studies of nucleation and growth during the atomic layer deposition of metals; Present Position: Apple
41. James Raiford (PhD 2021) Thesis Title: Engineering contact layers in metal halide perovskite solar cells using atomic layer deposition; Present Position: Noria Energy
42. Joel Schneider (PhD 2022) Thesis Title: Surface and subsurface reaction mechanisms in atomic layer deposition of metals and metal oxides; Present Position: Postdoc, University of Minnesota, Minneapolis
43. Tzu-Ling Liu (PhD 2022) Thesis Title: Investigating area-selective atomic layer deposition of dielectric on diverse substrate systems; Present Position: Postdoc, Stanford University
44. Sindhu Nathan (PhD 2022) Thesis Title: Understanding the role of catalyst structure in facilitating sustainable chemical production; Present Position: MRS/Optica Congressional Fellow, Washington DC
45. Jingwei Shi (PhD 2022) Thesis Title: Developing new chemistries and applications in molecular layer deposition; Present Position: Data Scientist, Lam Research
46. Solomon Oyakhire (PhD June 2023) Thesis Title: Surface science for improved lithium metal batteries; Present Position: Schmidt Science Fellow postdoc at UC Berkeley

47. Josiah Yarbrough (PhD June 2023) Thesis Title: Investigating the use of small molecule inhibitors for area-selective atomic layer deposition; Present Position: Medical student at Stanford University
48. Alex Shearer (PhD December 2024) Thesis Topic: Nucleation engineering of atomic layer deposition for nanoelectronic applications; Present Position: CTO at Arinna
49. Jacqueline Lewis (04/20– present) Thesis Topic: Hybrid organic-inorganic materials synthesis using layer-by-layer methods (Ph.D. student in Chemical Engineering)
50. Maggy Harake (04/21 – present) Thesis Topic: Area selective ALD with self assembled monolayers (Ph.D. student in Chemical Engineering)
51. Bang Nhan (03/22 – present) Thesis Topic: Atomic level design of heterogeneous catalysts: toward minimization of critical materials (Ph.D. student in Chemistry)
52. Sanzeeda Baig Shuchi (04/22 – present) Thesis Topic: Surface engineering for Li battery stability (Ph.D. student in Chemical Engineering)
53. Nadine Humphrey (04/22 – present) Thesis Topic: Atomic level design of heterogeneous catalysts: role of promoter and support (jointly advised with Simon Bare) (Ph.D. student in Chemical Engineering)
54. Alex Persson (04/22 – present) Thesis Topic: Hybrid organic-inorganic MLD for water splitting electrocatalysis (Ph.D. student in Chemical Engineering)
55. Genni Liccardo (04/22 – present) Thesis Topic: Atomic level design of heterogeneous catalysts: elemental and binary metals (jointly advised with Matteo Cargnello) (Ph.D. student in Chemical Engineering)
56. Kenzie Sanroman Gutierrez (04/23 – present) Thesis Topic: Investigating and improving lithium metal battery interfaces through ALD deposited interfacial films (Ph.D. student in Chemical Engineering)
57. Long Than (04/23 – present) Thesis Topic: Designing hybrid thin films for EUV lithography (Ph.D. student in Chemical Engineering)
58. Dea Fackovic Volcanjk (04/24 – present) Thesis Topic: Direct dielectric growth on 2D materials using ALD (Ph.D. student in Chemistry)
59. Anna Friederike Kolln (04/24 – present) Thesis Topic: Area selective ALD using vapor SAM inhibitors (Ph.D. student in Chemistry)
60. Lilliana Brandao (04/24 – present) Thesis Topic: Mechanistic studies of noble metal ALD on low surface energy substrates (Ph.D. student in Chemistry)
61. Bryce DeMuth (09/24 – present) Thesis Topic: Interface engineering for lithium sulfur batteries (Ph.D. student in Energy Science and Engineering)
62. Ololade Oriowo (04/25– present) Thesis Topic: Interface engineering for aqueous batteries (Ph.D. student in Chemical Engineering)

Masters Students Supervised

1. Sandeep Giri (MS 2006) Research: Spatially Distributed, Size Controlled Growth of Nanoparticles by Atomic Layer Deposition; Present Position: Manager, Google [X].
2. David Porter (MS 2006) Research: Chemical and Electronic Properties of the Interface during Atomic Layer Deposition; Present Position: Lam Research.
3. Sang Wook Park (MS 2010) Research: Development of Manganese Oxide as Catalyst Using Atomic Layer Deposition; Present Position: Manager, Applied Materials.

4. Richard Johnson (MS 2014) Research: Nucleation and growth mechanisms in ALD;
Present Position: Senior Process Engineer, Arcanum Alloys.

Postdoctoral Scholars Supervised

1. Szetsen Steven Lee, 1994 – 1996; Present Position: Professor, Chung Yuan Univ, Taiwan.
2. Andrew Teplaykov, 1996 – 1998; Present Position: Professor, University of Delaware.
3. Ilya Chizhov, 2000; Present Position: Software engineer.
4. Jeffrey King, 2006 – 2008; Present Position: Senior Research Scientist, Corning Incorporated.
5. Jon Servaites, 2011 – 2012; Present Position: Founder, eLucid Technology.
6. Han-Bo-Ram Lee, 2010 – 2013; Present Position: Assistant Professor, Incheon National University.
7. Scott Geyer, 2011– 2013; Present Position: Assistant Professor, Wake Forest University.
8. Jukka Tanskanen, 2009 – 2010, 2012 – 2013; Present Position: The Academy of Finland.
9. Carl Häggglund, 2010 – 2013; Present Position: Associate Senior Lecturer, Uppsala University, Sweden.
10. Chaiya Prasittichai, 2012 – 2014; Present Position: Lecturer, Kasetsart University, Thailand.
11. Sam Fleischman, 2012 – 2014; Present Position: Research Scientist, SynFuels China.
12. Adam Hultqvist, 2013 – 2015; Present Position: Researcher, Uppsala University, Sweden.
13. Pralay Santra, 2013 – 2015; Present Position: Scientist, Centre for Nano and Soft Matter Sciences, Bengaluru India.
14. Woo-Hee Kim, 2014 – 2016; Present Position: Assistant Professor, Department of Materials Science & Engineering, Chonbuk National University
15. Adrie Mackus, 2014 – 2016; Present Position: Assistant Professor, Eindhoven University, Netherlands.
16. Mie Lillethorup, 2015 – 2017; Present Position: CTO at RadiSurf, Denmark.
17. Uk Sim, 2016 – 2017; Present Position: Associate Professor, Korea Institute of Energy Technology (KENTECH), Korea.
18. Ariel Yi-Chun Jin, 2018 – 2019; Present Position: Scientist, Chilisin, Taiwan.
19. Li Zeng, 2017 – 2019; Present Position: Internal consulting team, Merck KGaA
20. Hayrensa Abulaiti, 2018 – 2021; Present Position: Applied Materials, Dielectric Deposition Group.
21. Il-Kwon Oh, 2018 – 2021; Present Position: Assistant Professor, Department of Electrical Engineering, Ajou University, Korea
22. Xiaoyun Yu, 2019 – 2020; Present Position: Zhangjiang Laboratory, China
23. Nathan Richey, 2018 – 2021; Present Position: Lehigh University
24. Amnon Rothman, 2021 – 2024; Present Position: Lecturer at Ben-Gurion University, Israel

25. Andreas Werbrouck, 2021 – 2023; Present Position: Postdoc at Univ of Missouri
26. Yujin Lee, 2021 – 2024; Present Position: Apple
27. Seunggi Seo, visiting postdoc from Yonsei University, 2021 – 2023; Present Position: Applied Materials
28. Miika Matinnen, visiting postdoc from University of Helsinki, 2022 – 2023; Present position: University of Helsinki, postdoc
29. Giulio D’Acunto, 2022 – 2025; Present Position: Postdoc at Eindhoven University
30. Tzu-Ling Liu, 2022 – present
31. Yukio Cho, 2023 – present (joint SLAC postdoc with Jagjit Nanda)
32. Madina Telkhozhayeva, 2024 – present
33. Yu-Sen Jiang, 2024 – present
34. Miso Kim, visiting postdoc from Hongik University, 2025 – present
35. Jeong-Min Lee, 2025 – present

Undergraduate Students Supervised

**Stanford undergraduates unless otherwise noted*

1. Mikhail Velikanov, NYU (9/94 – 5/95)
2. Julia Lyubovitsky, NYU (6/95 – 5/97)
3. Shawn Gibb, NYU (6/96 – 5/97)
4. Jaymin Jagmohan, NYU (1/97 – 5/97)
5. Michael Guo-Jie Wu, NYU (6/97 – 8/97)
6. Yetunde Noah, NYU (6/97 – 5/98)
7. Pratik Lal, NYU (6/97 – 5/98)
8. Florence Laine, NYU (7/97 – 5/98)
9. Sunay Shaw, NYU (1/98 – 5/98)
10. Mike Manzo, UC Berkeley (5/00 – 7/00)
11. John Tannaci (9/00 – 6/02)
12. Ryan Timmons (1/01 – 6/01)
13. Jim Van Deventer (6/02 – 6/04)
14. Aqueelah McKinley (6/02 – 6/03)
15. Helen Shi (1/03 – 6/04)
16. Greg Tsien (6/03 – 12/03)
17. Jimmy Lu (9/03 – 6/05)
18. Albert Keung (1/04 – 6/06)
19. Nathan Marchak (1/05 – 6/07)
20. Leslie Liang (1/05 – 6/06)
21. Allen Huang (1/05 – 12/05)

22. Ben Tran (4/06 – 12/08)
23. Michael Heath (4/06 – 6/08)
24. Kristin Squires (6/06 – 6/09)
25. Kristine Pangan-Okimoto (4/08 – 6/09)
26. Amita Seshadri (1/09 – 8/10)
27. Sonali Chopra (4/09 – 6/10)
28. Paul Chen (4/10 – 3/11)
29. William Tarpeh (9/10 – 12/11)
30. Juan Dominguez (9/10 – 6/12)
31. Thomas Joseph (6/11 – 9/11)
32. Weikang Sun (6/11 – 6/12)
33. Aaron Garg (1/11 – 6/13)
34. Peter Wang (6/12 – 6/13)
35. Qudus Lawal (1/13 – 12/13)
36. Troy Yang (4/13 – 6/14)
37. Mikhail Grant (6/13 – 12/13)
38. Allison Crow (1/14 – 6/16)
39. Takero Sone (6/14 – 6/16)
40. Pan Chuen (3/15 – 9/15)
41. Bradlee Birchansky (6/15 – 9/15)
42. China Kantner (4/16 – 6/16)
43. Charmayne Floyd (9/17 – 6/18)
44. Ben Fieron (4/18 – 12/19)
45. William Trevillyan (6/18 – 8/18)
46. Rayan Albraidi (6/19 – 6/20)
47. Cullen Chosy (9/19 – 6/21)
48. Ethan Amaya (6/21– 6/25)
49. Ajay Ravi (6/21– 6/23)
50. Jenny Han (6/22– 6/25)
51. Daniela Figueroa (4/23 – 5/25)
52. Eva Geierstanger (6/23 – 8/23)
53. Temitayo Ogunremi (6/24 – present)

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10. “Modeling performance of three-dimensional nanojunction photovoltaic devices,” A. Wangperawong and S. F. Bent, *Photovoltaic Specialists Conference (PVSC), 2011 36th IEEE*, June 2011, 002679 - 002682.
11. “Graded and alloyed II-VI semiconductors for photovoltaic buffer layers grown by atomic layer deposition (ALD),” J. R. Bakke, C. Häggglund, H. J. Jung, R. Sinclair, and S. F. Bent, *Photovoltaic Specialists Conference (PVSC), 2011 36th IEEE*, June 2011, 002691 – 002695.

12. “Chemical bath deposition and microstructuring of tin(II) sulfide films for photovoltaics,” S. M. Herron, A. Wangperawong, and S. F. Bent, *Photovoltaic Specialists Conference (PVSC), 2011 36th IEEE*, June 2011, 000368 – 000371.
13. “Recombination barrier layers in solid-state quantum dot-sensitized solar cells,” K. E. Roelofs, T. P. Brennan, J. C. Dominguez, and S. F. Bent, *Photovoltaic Specialists Conference (PVSC), 38th IEEE Photovoltaics Specialists Conference (PVSC)*, Austin, TX., June 2012, 003040-003043.
14. “Novel photoresist thin films with in-situ photoacid generator by molecular layer deposition,” H. Zhou and S. F. Bent, *Advances in Resist Materials and Processing Technology, Proc. of SPIE*, Vol. 8682, 86820U (2013). doi: 10.1117/12.2011572.
15. “Ab initio simulation of 1D pattern formation of adsorbates on the Ge(100)-2 × 1 surface,” B. Shong and S. F. Bent, *Mater. Res. Soc. Symp. Proc.*, Vol 1551 (2013). DOI: 10.1557/opl.2013.891.
16. “Molecular layer deposition of nanoscale organic films for nanoelectronics applications,” D. S. Bergsman, H. Zhou, and S. F. Bent, *Electrochemical Society Transactions*, 64 (9) (2014) 87-96. 10.1149/06409.0087ecst
17. “Area-selective atomic layer deposition of dielectric-on-dielectric for Cu/low-k dielectric patterns,” T.-L. Liu and S. F. Bent, *Proc. SPIE 10960, Advances in Patterning Materials and Processes XXXVI*, 109600O, (15 May 2019); doi: 10.1117/12.2519845
18. “Molecular layer deposition of an Al-based hybrid resist for electron-beam and EUV lithography,” A. Ravi, J. Shi, J. Lewis, and S. F. Bent, *Proc. SPIE 12498, Advances in Patterning Materials and Processes XL*, 124981B (30 April 2023); doi: 10.1117/12.2657636
19. “Achieving 1-nm-scale equivalent oxide thickness top gate dielectric on monolayer transition metal dichalcogenide transistors with CMOS-friendly approaches,” J.-S. Ko, A. Shearer, S. Lee, K. Neilson, M. Jaikissoon, K. Kim, S. Bent, K. Saraswat and E. Pop, *IEEE VLSI Tech. Symp.*, June 2024, Honolulu, HI.

Patents

- “Electrolyte additives inspired by atomic layer deposition for Lithium metal batteries”
S. Baig Shuchi, Y. Cui, S. F. Bent
Provisional Patent Application to be filed 2025-06-30
- “Advanced precursors for selective atomic layer deposition using self assembled monolayers”
I.-K. Oh, S. F. Bent
U.S. Patent Application 17/516,139, filed 2021-11-01
- “Solar Cell Comprising a Metal-Oxide Buffer Layer and Method of Fabrication”
K. A. Bush, A. F. Palmstrom, M. D. McGehee, S. F. Bent
U.S. Patent No. 11,296,244, issued 2022
- “Self-organizing Nanostructured Solar Cells”
S. F. Bent and B. M. Clemens

U.S. Patent No. 8,802,483 issued 2014

“Process for making layer-structured catalysts at the electrode/electrolyte interface of a fuel cell”

X. Jiang, X. Tian, F. B. Prinz, S. F. Bent, J. H. Shim, M. Sugawara, H. Huang

U. S. Patent No. 8,821,968 issued 2014

“Fabrication Method of Size-Controlled, Spatially Distributed Nanoparticles by Atomic Layer Deposition”

S. F. Bent, R. Chen, X. Jiang, Marja N. Mullings, Y. Saito

U.S. Patent No. 8,084,087, issued 2011

"Artificial Synapse Chip"

H. A. Fishman, D. Bloom, S. F. Bent, M. Peterman, J. Noolandi, and N. Mehenti

U.S. Patent No. 7,147,865, issued 2006

"Artificial Synapse Chip for Electronic Prosthetic Retina"

H. A. Fishman, M S. Blumenkranz, S. F. Bent, D. M. Bloom, M. C. Peterman

U.S. Patent No. 7,001,608, issued 2006

"Microfabricated Tissue as a Substrate for Pigment Epithelium Transplantation"

H. A. Fishman, M. Blumenkranz, S. F. Bent, C. Lee, P. Huie, Jr., and D. V. Palanker

U.S. Patent No. 6,939,378, issued 2005

Invited Lectures

1. Weizmann Institute of Science, Rehovot, Israel, 1989
2. AT&T Bell Laboratories, Murray Hill, NJ, 1991
3. IBM T. J. Watson Research Center, Yorktown Heights, NY, 1991
4. Universite Paul Sabatier, Toulouse, France, 1992
5. Wesleyan University, Physics Department, Middletown, CT, 1992
6. U. C. Berkeley, Department of Chemical Engineering, Berkeley, CA, 1993
7. Rutgers University, Laboratory for Surface Modification, Piscataway, NJ, 1995
8. PACE University, Department of Chemistry, Pleasantville, NY, 1997
9. U. C. Santa Barbara, Department of Chemistry, Santa Barbara, CA, 1997
10. Mid-Atlantic Regional Meeting of the ACS, Pleasantville, NY, 1997
11. Columbia University, Radiation Laboratory, New York, NY, 1997
12. College of Physicians and Surgeons, Columbia University, New York, NY, 1997
13. University of Southampton, Department of Chemistry, Southampton, England, 1997
14. St. John's University, Department of Chemistry, New York, NY, 1997
15. Lehigh University, Department of Chemistry, PA, 1997
16. Phi Lambda Upsilon Undergraduate Honor Society, New York University Chapter, New York, NY, 1997
17. City College of New York, Department of Chemistry, New York, NY, 1997
18. Queens College, Department of Chemistry, New York, NY, 1997
19. University of Wisconsin, Department of Chemistry, Madison, WI, 1997
20. University of Minnesota, Department of Chemistry, Minneapolis, MN, 1997
21. Barnard College, Department of Chemistry, New York, NY, 1997
22. University of Utah, Department of Chemistry, Salt Lake City, UT, 1997
23. Arizona State University, Department of Chemistry, Tempe, AZ, 1997
24. U. C. Irvine, Department of Chemistry, Irvine, CA, 1998
25. UCLA, Department of Chemical Engineering, Los Angeles, CA, 1998

26. U. C. San Diego, Department of Chemistry, San Diego, CA, 1998
27. Tufts University, Department of Chemistry, Boston, MA , 1998
28. California Institute of Technology, Department of Chemistry, Pasadena, CA, 1998
29. Stanford University, Department of Chemical Engineering, Stanford, CA, 1998
30. University of Colorado, Department of Chemical Engineering, Boulder, CO, 1998
31. University of Illinois, Chicago, Department of Chemistry, Chicago, IL, 1998
32. Telluride Meeting on Semiconductor Chemistry, Telluride, CO, 1998
33. 21st Surface/Interface Research Meeting of the Northern California Chapter of the American Vacuum Society, Davis, CA, 1998
34. 45th Annual Meeting of the American Vacuum Society, Baltimore, MD, 1998
35. Gordon Conference on Reactions at Surfaces, Ventura, CA, Discussion Leader, Feb. 28 - Mar. 1, 1999
36. *"Probing the Chemistry of Electronic Materials Processing,"* U. C. Berkeley, Department of Chemical Engineering, Berkeley, CA, March 17, 1999
37. *"Probing the Chemistry of Electronic Materials Processing,"* Purdue University, Department of Chemistry, IL, April 14, 1999
38. *"Chemical Modification of Semiconductor Surfaces by Cycloaddition Methods,"* Lucent Technologies, Bell Laboratories, Murray Hill, NJ, April 16, 1999
39. *"Chemical Modification of Semiconductor Surfaces by Cycloaddition Methods,"* U. C. Santa Cruz, Department of Chemistry, Santa Cruz, CA, May 26, 1999
40. *"Development of In Situ Diagnostics for Materials Processing,"* Beckman Young Investigators Conference, Beckman Center, Irvine, CA, August 21, 1999
41. *"A Mechanistic Picture of Growth and Microstructure Control of Amorphous Semiconductors,"* Fall Meeting of the American Chemical Society, New Orleans, LA, August 22-26, 1999
42. *"Investigating Reaction Mechanisms in Electronic Materials Processing,"* California Institute of Technology, Chemical Engineering Dept, Pasadena, CA, September 30, 1999
43. *"Investigating Reaction Mechanisms in Electronic Materials Processing,"* Department of Chemical Engineering, University of Texas, Austin, TX, February 1, 2000
44. *"Growth of Monolayer Organic Films on Semiconductor Substrates,"* Symposium on Surface Chemistry of Polymers and Organic Monolayers, Spring Meeting of the American Chemical Society, San Francisco, CA, April 26-30, 2000
45. *"Fundamental Aspects of Semiconductor Processing,"* 38th Annual Symposium, AIChE Northern California Section, Menlo Park, CA, April 21, 2000
46. *"Investigating Reaction Mechanisms in Electronic Materials Processing,"* Materials Science and Engineering Department, Stanford University, Stanford, CA, May 5, 2000
47. *"Peter Mark Memorial Award Lecture,"* 47th Annual Meeting of the American Vacuum Society, Peter Mark Memorial Award Lecture, Boston, MA, October 2-6, 2000
48. *"Functionalization and Growth of Electronic Materials,"* Department of Chemical Engineering, Massachusetts Institute of Technology, Cambridge, MA, Oct. 6, 2000
49. *"Functionalization of Silicon Surfaces,"* Symposium F: Nano- and Microcrystalline Semiconductor Materials and Structures, Materials Research Society, Fall Meeting, Boston, MA, November 29, 2000
50. *"Functionalization and Growth of Electronic Materials,"* Department of Chemistry, University of Pittsburgh, Pittsburgh, PA, December 1, 2000
51. *"Functionalization and Growth of Electronic Materials,"* Department of Chemical Engineering, U.C. San Diego, La Jolla, CA December 5, 2000
52. *"Synthetic Approaches for Molecular Functionalization of Semiconductor Surfaces,"* Gordon Research Conference on Reactions at Surfaces, Ventura, CA, Feb. 18-22, 2001
53. *"Integrating Organic Materials with Semiconductor Devices,"* 6th Annual Maria Goeppert-Mayer Interdisciplinary Symposium, San Diego Supercomputer Center at U. C. San Diego, La Jolla, California, March 3, 2001

54. *"Functionalization and Growth of Electronic Materials,"* Department of Chemical Engineering, North Carolina State University, Raleigh, NC, March 19, 2001
55. *"Functionalization and Growth of Electronic Materials,"* Department of Chemical Engineering, Carnegie Mellon University, Pittsburgh, PA, March 20, 2001
56. *"Identification of Radical Growth Precursors in Chemical Vapor Deposition,"* Symposium on Chemistry at Solid Surfaces, Spring Meeting of the American Chemical Society, San Diego, CA, April 1, 2001
57. *"Attaching Organic Molecules to Semiconductor Surfaces,"* Symposium on Molecules as Components in Electronic Devices, Spring Meeting of the American Chemical Society, San Diego, CA, April 2, 2001
58. *"Organic Modification of Semiconductor Interfaces,"* Gordon Research Conference on Chemical Sensors and Interfacial Design, Il Ciocco, Italy, May 6-10, 2001
59. *"Functionalization and Growth of Electronic Materials,"* Department of Chemical Engineering, U. C. Santa Barbara, Santa Barbara, CA, May 31, 2001
60. *"Growth and Processing of SiC-Based Materials,"* Applied Materials, LPCVD and CVD Low k Product Units, Santa Clara, CA, June 26, 2001
61. *"Strategies for Organic Modification of Semiconductor Surfaces,"* Gordon Research Conference on Chemistry of Electronic Materials, New London, CT, July 15-19, 2001
62. *"Evidence for Cycloaddition Chemistry at Semiconductor Surfaces,"* 10th International Symposium on Novel Aromatics (ISNA-10), U. C. San Diego, La Jolla, CA, Aug. 7, 2001
63. *"Interface Engineering for Materials and Biological Applications,"* Roundtable Meeting, Center for Integrated Systems, Stanford University, Nov. 13, 2001
64. *"Interface Engineering for Materials and Biological Applications,"* U. C. Santa Barbara, Santa Barbara, CA, Feb. 8, 2002
65. *"Using Chemistry to Modify the Semiconductor Interface,"* Nanotechnology Symposium Series, University of Washington, Seattle, WA, February 19, 2002
66. *"Integrating Organic Materials with Silicon and Germanium,"* 5th Annual Flory Conference, Stanford University, Stanford, CA, February 22, 2002
67. *"Intermediates and Reaction Mechanisms in Amorphous and Microcrystalline Silicon Film Growth,"* Symposium A: Amorphous and Heterogeneous Silicon-Based Films, Materials Research Society, Spring Meeting, San Francisco, April 2-5, 2002
68. *"Interface Engineering for Materials and Biological Applications,"* Chemistry Division Colloquium, Naval Research Laboratory, Washington D.C., Apr. 10, 2002
69. *"A Molecular View of Semiconductor Processing,"* Department of Chemistry, University of Missouri, Columbia, MO, May 10, 2002
70. *"Engineering a New Pathway for Vision,"* South Bay AIChE Meeting, Silicon Valley, CA, May 22, 2002
71. *"Using Spectroscopy to Shed Light on Electronic Materials Processing,"* 56th International Symposium on Molecular Spectroscopy, Ohio State University, Columbus, Ohio, June 17-26, 2002
72. *"Using Chemistry to Modify the Semiconductor Interface,"* Department of Chemical Engineering, UCLA, Los Angeles, CA, July 11, 2002
73. *"Integrating Organic Materials with Silicon and Germanium,"* Gordon Research Conference on Electronic Processes in Organic Materials, Newport, Rhode Island, July 21-26, 2002
74. *"Interface Engineering for Materials and Biological Applications,"* Fourth Annual Beckman Scholars Symposium, Beckman Center, Irvine, CA, July 25-27, 2002
75. Telluride Workshop on Semiconductor Surface Chemistry, Telluride, CO, July 28-Aug 2, 2002
76. *"Integrating Organic Materials with Semiconductor Surfaces,"* Chemical and Materials Science Seminar, Stanford Synchrotron Radiation Laboratory, Stanford, CA, August 14, 2002

77. *"Detecting Reactive Species in Hot-Wire CVD of Si-Based Films,"* 2nd International Conference on Cat-CVD (Hot-Wire CVD) Process, Denver, CO, September 10-13, 2002
78. *"Using Spectroscopy to Shed Light on Electronic Materials Processing,"* Society for Applied Spectroscopy, Northern California Section, Mountain View, CA, September 18, 2002
79. *"Bringing Organic Chemistry to the Surface,"* Plenary Lecture, Southern California Chapter of the American Vacuum Society, Leading Edge Student Symposium, Anaheim, CA, October 2, 2002.
80. *"Integrating Organic Materials with Semiconductor Surfaces,"* Xerox PARC seminar, Palo Alto, CA, October 18, 2002.
81. *"Bringing Organic Chemistry to the Surface,"* Department of Chemistry, Harvard University, Cambridge, MA, November 14, 2002.
82. *"Organic Functionalization of Semiconductor Surfaces,"* University of California Surface Science Symposium, U. C. Riverside, Riverside, CA, February 13-14, 2003
83. *"Emerging Opportunities in New Dielectric Materials and Processes for the Future of Semiconductor Manufacturing,"* Flory Conference on Novel Electronic Materials, Stanford University, Stanford, CA, February 20-21, 2003.
84. *"Reactions at Semiconductor Surfaces: From Organic Monolayers to Templated Deposition,"* March Meeting of the American Physical Society, Austin, TX, March 3-7, 2003.
85. *"Semiconductor Surface Functionalization and Application to Atomic Layer Deposition,"* Department of Chemistry, Washington University, St. Louis, MO, April 3, 2003.
86. *"The Molecular Nature of Semiconductor Surfaces,"* Department of Chemistry, Columbia University, New York, NY, May 8, 2003.
87. 4th Annual Entrepreneur's Day (EDAY), School of Engineering, Stanford University, Stanford, CA, May 17, 2003.
88. *"Interface Engineering for Retinal Prosthetics,"* Nano and Bio-Nanoscience Research Meeting, Northern California Chapter of the AVS, University of California, Berkeley, June 11, 2003.
89. *"Elucidating Adsorption Mechanisms at the Semiconductor Interface,"* 226th National Meeting of the American Chemical Society, Colloid and Surface Chemistry Division, New York, NY, Sept 7-11, 2003.
90. *"What is a Course on Spectroscopy Doing in the Chemical Engineering Curriculum?"* 226th National Meeting of the American Chemical Society, Divisions of Chemical Education and Physical Chemistry, New York, NY, Sept 7-11, 2003.
91. *"Engineering Interfaces for Vision Restoration,"* Advanced Technology Lecture Series, Hewlett-Packard, Corvallis, OR, Sept 17, 2003.
92. *"Chemical Strategies for Organic Functionalization of Semiconductors,"* Pacific Northwest Chapter of the American Vacuum Society, Portland, OR, Sept 18-19, 2003.
93. *"Surface Modification for Area-Selective Atomic Layer Deposition,"* Department of Chemical Engineering, University of Delaware, Newark, DE, Nov 7, 2003.
94. Women in Chemical Engineering: Profiles and Motion; Panel Discussion at the National Meeting of the American Institute of Chemical Engineers, San Francisco, CA, Nov 16, 2003.
95. *"Organic Functionalization of Semiconductor Surfaces,"* Hewlett-Packard, Palo Alto, CA, December 12, 2003.
96. *"Understanding Molecular Reactivity at the Semiconductor Surface,"* Willard Davis Lecture, Department of Chemistry and Biochemistry, University of South Carolina, Columbia, SC, Jan 16, 2004.
97. Retinal Prostheses, Stanford Bioengineering Faculty Spotlight, Stanford University, Stanford, CA, Jan 28, 2004.

98. *"Reactions at Semiconductor Surfaces: From Organic Monolayers to Selective Deposition,"* Department of Chemical Engineering, University of Wisconsin, Madison, WI, Feb 3, 2004.
99. *"Carbonyl Chemistry at the Ge(100)-2x1 Surface: Spectroscopic Identification of Complex Reaction Products,"* 227th National Meeting of the American Chemical Society, Symposium on Vibrational Analyses of Dry and Wet Surfaces, Division of Colloid and Surface Chemistry, Anaheim, CA, March 28-April 1, 2004.
100. *"Organic Functionalization of Inorganic Semiconductors,"* 227th National Meeting of the American Chemical Society, Symposium on Surface Chemistry of Inorganic Materials, Division of Inorganic Chemistry, Anaheim, CA, March 28-April 1, 2004.
101. *"Engineering Interfaces for Vision Restoration,"* Stanford 2004 Biotechnology Conference, Stanford University, July 23, 2004.
102. *"Area Selective ALD of High κ Dielectrics,"* ALD 2004 Conference, Helsinki, Finland, August 16-18, 2004.
103. *"Atomic Layer Deposition of High- κ Dielectrics: Substrate Preparation, Precursor Selection, and Process Conditions,"* with Charles B. Musgrave, Stanford Engineering and Science Institute 2004, Short Course on New Electronic Materials for Extending Moore's Law, August 23-27, 2004.
104. *"Micropatterning Proteins on Substrates to Direct Cell Growth for Neural Prostheses,"* SPIE Conference on Nanosensing: Materials and Devices (OE103), Symposium on Functionalization and patterning of inorganic surfaces with biomolecules and bio-organisms for sensing, Philadelphia, PA, October 25-28, 2004.
105. *"Reactions at Semiconductor Surfaces: From Organic Monolayers to Selective Atomic Layer Deposition,"* Laboratory for Surface Modification Seminar Series, Rutgers University, Piscataway, NJ, October 28, 2004.
106. *"Area Selective Atomic Layer Deposition,"* AIChE Meeting, Plenary Session, Materials Engineering and Science Division, Austin, TX, Nov 7-12, 2004.
107. *"Functionalization of Semiconductor Surfaces,"* 51st International Symposium of the American Vacuum Society, Anaheim, CA, Nov 14-19, 2004.
108. *"Layer by Layer Organic Functionalization of Semiconductors,"* 229th National American Chemical Society Meeting, San Diego, CA, Mar 13-17, 2005.
109. *"Time-Dependent Behavior in the Adsorption of Model Organic Compounds on Ge(100)-2x1,"* Materials Research Society, Spring Meeting, Symposium on In situ Studies of Gas/Solid Surface Reaction Dynamics, San Francisco, March 28-April 1, 2005.
110. *"Gaining Control of Electronic Materials: from Functionalizing Surfaces to Making Devices,"* Student Seminar Series, Department of Chemistry, University of Minnesota, Minneapolis, MN, April 5, 2005.
111. *"Reactions at Semiconductor Surfaces: From Organic Monolayers to Selective Atomic Layer Deposition,"* Department of Chemistry, Princeton University, Princeton, NJ, April 7, 2005.
112. *"Reactions at Semiconductor Surfaces: From Organic Monolayers to Selective Atomic Layer Deposition,"* Surface Science and Catalysis Seminar Series, U.C. Berkeley, Berkeley, CA, April 21, 2005.
113. *"Layer by Layer Molecular Functionalization of Semiconductors,"* International Conference on Materials for Advanced Technologies (ICMAT-2005), Materials Research Society of Singapore, Singapore, July 3-8, 2005.
114. *"Bringing Organic Chemistry to the Surface,"* Department of Chemistry, Carleton College, Northfield, MN, Sept 16, 2005.
115. *"Area Selective Atomic Layer Deposition of Electronic Materials,"* Joint Symposium on Nanoscale Materials, Processes and Devices, Kona, Hawaii, November 3-4, 2005.

116. “*Chemical Modification of Semiconductor Surfaces: Basic Principles and Applications*,” 4th International Symposium on Surface Science and Nanotechnology (ISSS-4), Omiya, Saitama, Japan, November 14-17, 2005.
117. “*Overview of ALD, Area Selective ALD, and ALD of Catalysts*,” Honda Research and Development Center, Wako, Japan, November 17, 2005.
118. “*Surface Functionalization for Area Selective Atomic Layer Deposition*,” Microscopy and Microanalysis Seminar Series, Chalmers University, Gothenburg, Sweden, March 10, 2006.
119. “*Chemical Functionalization of Semiconductor Surfaces*,” Department of Physics, Technical University of Denmark, Lyngby, Denmark, May 24, 2006.
120. “*Organic Functionalization of Semiconductor Surfaces*,” Telluride Workshop on Chemical Modification of Semiconductor Surfaces, Telluride, CO July 31- Aug. 4, 2006.
121. “*Unraveling Carbonyl Chemistry on Ge(100)-2x1 Using Vibrational Spectroscopy*,” Advanced Vibrational Spectroscopy Studies on Organic, Polymer, and Biological Surfaces, 232nd ACS National Meeting, San Francisco, CA, September 10-14, 2006.
122. “*Atomic Layer Deposition of Electrocatalytic Platinum for Solid Oxide Fuel Cells*,” Second Symposium on Atomic Layer Deposition Applications, 210th Meeting of the Electrochemical Society, Cancun, Mexico, Oct 29-Nov 3, 2006.
123. “*Surface Functionalization for Selective Area ALD*,” 53rd International Symposium of the American Vacuum Society, San Francisco, CA, Nov 12-17, 2006.
124. “*Elucidating Carbonyl Chemistry on Ge(100)-2x1*,” AIChE Meeting, San Francisco, CA, Nov 12-17, 2006.
125. “*Surface Functionalization for Area Selective Atomic Layer Deposition*,” Sandia National Laboratory, Albuquerque, NM, February 21, 2007.
126. “*Organic Chemistry at the Semiconductor Surface*,” Fourth San Luis Conference on Surfaces, Interfaces and Catalysis, Cuernavaca, Mexico, April 14-22, 2007.
127. “*Surface Functionalization for Selective Area ALD*,” Intel Corporation, Teleseminar, May 20, 2007.
128. “*Preventing Blindness: Retinal Implants*,” E-Day 2007, Engineering From Head to Toe, School of Engineering, Stanford University, Stanford, CA, July 21, 2007.
129. “*Organic Functionalization of Semiconductor Surfaces*,” 11th International Conference on the Formation of Semiconductor Interfaces (ICFSI - 11), Manaus - Amazonas, Brazil August 19-24, 2007.
130. “*Understanding Area Selective ALD*,” EuroCVD 16 Conference, Den Haag, The Netherlands, Sept 16-21, 2007.
131. “*Inorganic Nanocomposite Solar Cells*,” GCEP Research Symposium, Stanford University, Stanford, CA Oct 2, 2007.
132. “*Modifying Electronic Materials: from Functionalizing Surfaces to Making Devices*,” Department of Chemical Engineering, Pennsylvania State University, State College, PA, Oct 4, 2007.
133. “*Molecular Approaches to Modifying Semiconductor Surfaces*,” Materials Science Institute Retreat, University of Oregon, Salishan Lodge, Glendon Beach, OR, Dec 11-13, 2007.
134. “*Modifying Electronic Materials: from Functionalizing Surfaces to Making Devices*,” Distinguished Lecturer Series, Department of Chemical Engineering, University of Utah, Salt Lake City, UT, Feb 19, 2008.
135. “*Understanding and Exploiting Molecular Bonding at the Semiconductor Surface*,” Department of Chemistry, Johns Hopkins University, Mar 18, 2008.
136. “*Exploring Atomic Layer Deposition for Catalysis and Energy Applications*,” Department of Materials Science and Engineering, and NanoCenter, University of Maryland, College Park, MD, Mar 19, 2008.

137. *"Understanding and Exploiting Molecular Bonding at the Semiconductor Surface,"* Department of Chemistry, University of Delaware, Newark, DE, Mar 21, 2008.
138. *"Exploring Atomic Layer Deposition for Catalysis and Energy Applications,"* Department of Chemical Engineering, Colorado School of Mines, Golden, CO, Mar 28, 2008.
139. *"Combining Quantum Chemistry with Vibrational Spectroscopy to Elucidate Bonding at the Organic-Semiconductor Interface,"* Computational Spectroscopy Symposium, Physical Chemistry Division, 235th National American Chemical Society Meeting, New Orleans, LA, Apr 6-10, 2008.
140. *"Molecular Approaches to Modifying Surfaces,"* Department of Chemistry, Seoul National University, Seoul, Korea, April 14, 2008.
141. *Molecular Approaches to Modifying Surfaces,"* Korea Advanced Institute of Science and Technology (KAIST), Seoul, Korea, April 16, 2008.
142. *"Molecular Approaches to Modifying Surfaces,"* Nano-Energy Fusion Physical Chemistry Symposium, Korean Chemical Society Meeting, Seoul, Korea, April 17-18, 2008.
143. *"Preventing Blindness: Retinal Implants,"* Medical School Reunion Weekend, Stanford University, Stanford, CA, April 26, 2008.
144. *"Powering the Future with Sustainable Energy,"* Summer Science Lecture Series, Stanford University, August 21, 2008.
145. *"Solar Energy,"* Energy Supply Panel, Woods/Precourt Affiliate Conference, Stanford University, Stanford, CA, September 12, 2008.
146. *"Exploring Atomic Layer Deposition for Catalysis and Energy Applications,"* Department of Chemical Engineering, U.C. Berkeley, California, Oct 15, 2008.
147. *"Area Selective Atomic Layer Deposition,"* Molecular Foundry, Lawrence Berkeley National Laboratory, Berkeley, California, Jan 6, 2009.
148. *"Solar Energy,"* Horn Lecture Panel on "Fueling the Future", Woods Institute, Stanford University, Stanford, CA, Jan 20, 2009.
149. *"Forming Catalysts by Atomic Layer Deposition: from Thin Films to Nanoparticles"* Department of Chemical and Biological Engineering, Drexel University, Philadelphia, PA, Feb 27, 2009.
150. *"The Role of Dative Bonding in Reactions at Semiconductor Surfaces,"* Gordon Research Conference on Inorganic Reaction Mechanisms, Galveston, TX, March 8, 2009.
151. *"Earth Abundant Chalcogenide Materials for Thin Film PV,"* SPRC Workshop on Inorganic Thin Film Materials: Toward Grid Parity, Stanford, CA, March 14, 2009.
152. *"Forming Catalysts by Atomic Layer Deposition: from Thin Films to Nanoparticles,"* Lawrence Livermore National Laboratory, Livermore, CA, April 21, 2009.
153. *"New Approaches to Making Materials for Sustainable Energy"* Department of Mechanical Science and Engineering, University of Illinois, Urbana-Champaign, IL, April 28, 2009.
154. *"New Approaches to Making Materials for Sustainable Energy Devices,"* Department of Chemical Engineering, University of California, Riverside, CA, May 8, 2009.
155. *"The Future of Energy,"* presentation with Sally Benson, Leading Matters San Francisco, San Francisco, CA, May 9, 2009.
156. *"The Undergraduate Research Experience: Friend or Foe?"* Award Winning Teachers on Teaching, Stanford University, Stanford, CA, May 14, 2009.
157. *"Organic Barrier Layers Using Molecular Layer Deposition,"* SRC E-Workshop, June 25, 2009.
158. *"Making Solar Power Affordable,"* E-Day 2009, School of Engineering, Stanford University, Stanford, CA, July 11, 2009.
159. *"Molecular Approaches to Modifying Semiconductor Surfaces,"* Trinity College, Dublin, Ireland, October 2, 2009.

160. *"DOE Energy Frontier Research Center on Nanostructuring for Efficient Energy Conversion (CNEEC),"* DOE Synthesis and Processing Sciences Contractors Meeting, Arlington, Virginia, October 26-28, 2009.
161. *"DOE Energy Frontier Research Center on Nanostructuring for Efficient Energy Conversion (CNEEC),"* 56th International Meeting of the AVS, San Jose, CA, Nov 8-13, 2009.
162. *"Materials for Thin Film Photovoltaics,"* 2010 Stanford University Photonics Retreat, Napa, CA, April 10, 2010.
163. *"DOE Energy Frontier Research Center on Nanostructuring for Efficient Energy Conversion (CNEEC),"* Workshop on Photovoltaics, Center for Emerging Energy Technologies (CEET), University of New Mexico, Albuquerque, NM, April 19, 2010.
164. *"Chalcogenide Thin Film Photovoltaics,"* Department of Chemical and Nuclear Engineering, University of New Mexico, Albuquerque, NM, April 20, 2010.
165. *"Nanostructuring for Efficient Energy Conversion,"* Stanford Energy Seminar, Stanford University, Stanford, CA, May 26, 2010.
166. Telluride Workshop on Semiconductor Surface Chemistry, Telluride, CO, July 26-30, 2010.
167. *"Comparison of HWCVD and MLD approaches for forming nanoscale organic thin films,"* Sixth International Conference on Hot-Wire Chemical Vapor Deposition (Cat-CVD) Process, Ecole Polytechnique, Palaiseau, France, September 13-17, 2010.
168. *"Molecular Layer Deposition of Organic Thin Films for Copper Diffusion Barriers,"* ITRS-Emerging Research Materials Workshop on Ultrathin Cu Barriers, e-Workshop, September 23, 2010.
169. *"Earth Abundant Chalcogenide Materials for Thin Film PV,"* ECS Symposium on Photovoltaics for the 21st Century 6, Las Vegas, NV, Oct 10-15, 2010.
170. *"Engineering interfaces for energy conversion,"* Department of Chemical Engineering, Caltech, Pasadena, CA, November 4, 2010.
171. *"Investigating interfacial barrier layers in quantum dot and dye sensitized solar cells,"* Gordon Conference on Chemical Reactions at Surfaces, Ventura, CA, February 6-11, 2011.
172. *"Nanostructuring for efficient energy conversion,"* Plenary talk, AAAS Annual Meeting, Washington, D.C., 17-21 February, 2011.
173. *"Engineering interfaces for photovoltaic energy conversion,"* Materials for Energy Applications Session, 2011 March Meeting of the American Physical Society, Dallas, TX, March 21-25, 2011.
174. *"Engineering interfaces for efficient solar energy conversion,"* Nanotechnology and Materials Seminar Series, Department of Chemistry, University of Texas, Austin, TX, March 30, 2011.
175. *"Functionalizing Surfaces for Efficient Solar Energy Conversion,"* Department of Chemistry, University of Calgary, BC, Canada, April 1, 2011.
176. *"Functionalizing Surfaces for Efficient Solar Energy Conversion,"* Department of Chemistry, University of California, Irvine, April 26, 2011.
177. *"Functionalizing Surfaces for Efficient Solar Energy Conversion,"* Department of Chemistry, Northwestern University, Evanston, IL, May 4, 2011.
178. *"Modifying interfaces for efficient solar energy conversion,"* 242nd American Chemical Society National Meeting, Denver, CO, August 28 - September 1, 2011.
179. *"Nanoscale Materials for Sustainable Energy,"* Energy@Stanford & SLAC Summer Conference, Stanford, CA, Sept 12-16, 2011.
180. *"Molecular Layer Deposition of Nanoscale Organic Films for Copper Diffusion Barriers"* Advanced Metallization Conference 2011, San Diego, CA, October 4-6, 2011.

181. *“Improving solar energy conversion with nanoscale materials,”* AIP-AVS Industrial Physics Forum on Energy: Transition to a sustainable future, AVS National Meeting, Nashville TN, Oct 31-Nov. 1, 2011.
182. *“Nanoscale materials for efficient energy conversion,”* Energy and Environment Affiliates Program Conference, Stanford University, Stanford, CA, Nov 2-3, 2011.
183. *“Improving solar energy conversion with nanoscale materials,”* Africa MRS Meeting, Victoria Falls City, Zimbabwe, December 11-17, 2011.
184. *“Engineering Interfaces for Energy Conversion and Nanoelectronics,”* Department of Chemical Engineering, University of Southern California, Los Angeles, CA, February 9, 2012.
185. *“Improving Energy Conversion with Nanoscale Materials and the CNEEC EFRC Program,”* Keynote speech, Japan NANO 2012 Symposium, Tokyo, Japan, February 17, 2012.
186. *“Cheap and Thin: Two Processing Approaches to Manufacturable Solar Cells,”* Symposium V on Advanced Materials Processing for Scalable Solar Cell Manufacturing II, Spring Meeting of the Materials Research Society, San Francisco, CA, April 9-13, 2012.
187. *“Applications of Atomic Layer Deposition to Photovoltaics,”* Miasole, Sunnyvale, CA May 8, 2012.
188. *“Nanoparticles by ALD: From Nucleation Mechanisms to Applications in Quantum Dot Solar Cells,”* 12th International Conference on Atomic Layer Deposition (AVS-ALD), Dresden, Germany, June 17-20, 2012.
189. *“Functionalizing Semiconductor Surfaces by Monolayer and Multilayer Chemistry,”* International Conference on Solid Films and Surfaces (ICSFS 16), Genoa, Italy, July 1-6, 2012.
190. *“Functionalizing Solid Surfaces by Monolayer and Multilayer Chemistry: From Fundamentals to Applications,”* 244th ACS National Meeting, Philadelphia, PA, August 19-23, 2012.
191. *“Controlling deposition in ALD: From continuous films to nanoparticles, and applications in energy conversion,”* Workshop on New Frontiers in Plasma Nanopatterning Sponsored by The Molecular Foundry / Oxford Instruments, Lawrence Berkeley National Laboratory, Berkeley, CA, October 3rd, 2012.
192. *“Nanoparticles and quantum dots: from nucleation mechanisms to applications in solar cells,”* Chemical and Biomolecular Engineering Colloquium, U. C. Berkeley, Berkeley, CA, November 14, 2012.
193. *“Atomic Layer Deposition: Nucleation, Growth, and Applications,”* Applied Materials, December 17, 2012.
194. Gordon Conference on Nanomaterials for Energy-Conversion: Electrochemical Energy Conversion and Storage, Ventura, CA, Discussion Leader, Feb. 3-8, 2013.
195. *“Challenges and Solutions for More Sustainable Energy Systems,”* Keynote Speech, Symposium on Technology for Clean Energy, Northern California AVS Joint User Group Topical Conference, San Jose, CA, Feb. 21, 2013.
196. *“Designing catalysts using layer by layer growth,”* Surface Science and Catalysis Seminar Series, U.C. Berkeley, Berkeley, CA, February 28, 2013.
197. Research Partnership Workshop on Water, Energy and the Environment for Women Scientists from the U.S., Morocco, Algeria and Tunisia, Casablanca, Morocco, March 5-8, 2013.
198. *“Functionalizing Semiconductor Surfaces by Monolayer and Multilayer Chemistry: Toward Control of Nanoscale Materials,”* Symposium on Surfaces of Nanoscale Semiconductors, 2013 Spring Meeting of the Materials Research Society, San Francisco, CA, March 31- April 5, 2013.

199. *"Presidential Commission on Graduate Education,"* 245th ACS National Meeting, New Orleans, LA, April 7-11, 2013.
200. *"Modifying Interfaces for Energy Conversion and Nanoelectronics,"* Department of Chemical Engineering, University of Rochester, Rochester, NY, April 17, 2013.
201. *"The Potential for ALD to Meet Future Energy Challenges,"* Future of ALD-DARPA Workshop, Chicago, IL, April 20-21, 2013.
202. *"Reactions of Organic Molecules at the Germanium Surface,"* Plenary Talk, 14th International Conference on the Coordination and Organometallic Chemistry of Germanium, Tin and Lead, Cape Breton, Nova Scotia, Canada, July 14-19, 2013.
203. *"Nanoparticles and quantum dots: from nucleation mechanisms to applications in solar cells,"* Okinawa Institute of Science and Technology, Okinawa, Japan, September 11-13, 2013.
204. *"Molecular Layer Deposition of Organic Films for Nanoelectronics Applications,"* 60th Annual f International Symposium, Long Beach, CA, Oct 27-Nov 1, 2013.
205. *"Manganese oxide oxygen evolution catalysts deposited by ALD,"* Symposium on "Nanomaterials for Energy Capture, Conversion, and Storage", Inorganic Chemistry Division, Spring 2014 ACS National Meeting, Dallas, TX, 16-20 March 2014.
206. *"Strategies for selective deposition of organic and inorganic materials on patterned substrates,"* Symposium on "Molecular Processes for Selective Deposition, Modification, Placement and Assembly of Nanostructures", Colloid and Surface Chemistry Division, Spring 2014 ACS National Meeting, Dallas, TX, 16-20 March 2014.
207. *"Understanding nucleation in metal ALD,"* Ultratech ALD User Group meeting, Stanford University, Stanford, CA, April 1-2, 2014.
208. *"Selective Deposition of Dielectrics,"* SRC e-workshop, April 17, 2014.
209. *"Molecular Layer Deposition of Organic and Hybrid Films for Interconnect Technologies,"* Symposium on Advanced Interconnects for Micro- and Nanoelectronics–Materials, Processes, and Reliability, 2014 Spring Meeting of the Materials Research Society, San Francisco, CA, April 21-25, 2014.
210. *"Improving Energy Conversion with Nanoscale Materials,"* Department of Energy Resources Engineering, Stanford University, Stanford CA, April 28, 2014.
211. *"ALD Materials for Energy Conversion,"* CIS Roundtable Meeting, Stanford University, Stanford, CA, May 13, 2014.
212. *"Atomic Layer Deposition: From Fundamental Mechanisms to Applications in Sustainable Energy,"* Materials Science Special Colloquium, Argonne National Laboratory, Lemont, IL, June 5, 2014.
213. *"Shining Light on Energy,"* Leonardo Art Science Evenings (LASERs), Stanford University, Office of Science Outreach and the Arts Program, June 12, 2014.
214. *"Designing catalysts using layer by layer growth,"* SUNCAT Industrial Affiliates Program, Stanford University, Stanford, CA, June 12, 2014.
215. *"Quantum Dot Solar Cells,"* 4th Sungkyun International Solar Forum (SISF 2014), Sungkyunkwan University, Seoul, Korea, July 5-7, 2014.
216. *"Improving energy conversion with nanoscale materials,"* Yonsei University, Seoul, Korea, July 7, 2014.
217. *"Improving energy conversion with nanoscale materials,"* Department of Energy Sciences, Sungkkyunkwan University (SKKU), Seoul, Korea, July 8, 2014.
218. *"Role of Molecular Structure in Organic Functionalization of Semiconductor Surfaces,"* Telluride Workshop on Semiconductor Surface Chemistry, Telluride, CO, July 28-Aug 1, 2014.
219. *"Fundamentals of Nucleation in Atomic Layer Deposition,"* Telluride Workshop on Semiconductor Surface Chemistry, Telluride, CO, July 28-Aug 1, 2014.
220. *"Role of Molecular Structure in Surface Chemical Reactivity,"* Symposium on "Advances in Molecular–Level Understanding of Surface Reactivity" Colloid and

- Surface Chemistry Division, 2014 Fall ACS National Meeting, San Francisco, CA, Aug 10-14, 2014.
221. *"Molecular Functionalization of Semiconductor Surfaces,"* 30th European Conference on Surface Science, ECOS-30, Antalya, Turkey, August 31–September 5, 2014.
222. *"Improving Energy Conversion with Nanoscale Materials,"* Energy@Stanford & SLAC Summer Conference, Stanford, CA, Sept 1, 2014.
223. *"Molecular Layer Deposition of Nanoscale Organic Films for Nanoelectronics Applications,"* 226th Electrochemical Society Fall Meeting, Cancun, Mexico, Oct. 5-10, 2014.
224. *"Understanding and Improving Solar Energy Conversion through Interface Engineering,"* PacSurf 2014, Kohala Coast, Hawaii, Dec 7-11, 2014.
225. *"Atomic Layer Deposition of Nanoscale Materials for Energy Conversion Applications,"* Center for Condensed Matter Science, National Taiwan University, Jan 27, 2015.
226. *"Atomic Layer Deposition of Nanoscale Materials for Energy Conversion Applications,"* Instrument Technology Research Center (ITRC), Taipei, Taiwan, Jan 28, 2015.
227. *"Atomic Layer Deposition: From Fundamentals to Applications,"* Keynote talk, Physical Society Republic of China, 2015 Annual Meeting - AVS Taiwan Chapter Session, Taipei, Taiwan, Jan 29, 2015.
228. *"Improving Energy Conversion with Nanoscale Materials,"* Molecular Foundry, Lawrence Berkeley National Laboratory, Berkeley, CA, February 3, 2015.
229. Gordon Conference on Chemical Reactions at Surfaces, Ventura, CA Discussion Leader, February 8-12, 2015.
230. *"Powering the Future with Sustainable Energy: How Do We Get There?"* Stanford Parents Weekend 2015, Stanford, CA, February 28, 2015.
231. *"Tuning the Properties of Quantum Dot Solar Cells by Surface Functionalization,"* Symposium on "The interplay of structure and carrier dynamics in energy-relevant nanomaterials" 2015 MRS Spring Meeting, San Francisco, CA, April 6 – 10, 2015.
232. *"Molecular Functionalization of Semiconductor Surfaces,"* Colloquium, Center on Structure and Dynamics of Internal Interfaces, Philipps-Universität Marburg, Marburg, Germany, April 28, 2015.
233. *"The Role of Interface Engineering in Next Generation Photovoltaics,"* From the Witches Cauldrons in Materials Science, Goslar, Germany, April 29-30, 2015.
234. *"Molecular Functionalization of Semiconductor Surfaces: From Single Crystals to Quantum Dots,"* 8th Biennial International Conference on Materials for Advanced Technologies (ICMAT), Symposium on Surfaces/Interfaces Modification by Molecules, Singapore, June 28-July 3, 2015.
235. *"Nucleation in Atomic Layer Deposition: From Fundamentals to Applications,"* Intermolecular, San Jose, CA, July 16, 2015.
236. *"Applications of Atomic and Molecular Layer Deposition: Toward Catalysts, Solar Cells, and Nanoelectronics,"* 1st International Conference on Applied Surface Science (ICASS), Shanghai, China, July 27-30, 2015, plenary talk.
237. *"Designing Catalysts using Layer by Layer Growth,"* Energy@Stanford & SLAC Summer Conference, Stanford, CA, Sept 10, 2015.
238. *"Nanoscale Materials for Energy Conversion,"* Institute of Materials Science and Engineering (IMSE) Seminar Series, Washington University in St. Louis, St. Louis, MO, October 9, 2015.
239. *"Molecular Functionalization of Semiconductor Surfaces: From Single Crystals to Quantum Dots,"* 62nd Annual International AVS Symposium, San Jose, CA, October 18 – 23, 2015.
240. *"Controlled Synthesis and Study of Nanoscale Materials for Energy Conversion,"* Department of Chemical and Biological Engineering, Tufts University, Medford, MA, November 30, 2015.

241. *“Controlled Synthesis and Study of Nanoscale Materials for Energy Conversion,”* Department of Chemical and Biomolecular Engineering, Cornell University, Ithaca, NY, February 1, 2016.
242. *“Nanoscale Materials for Sustainable Energy,”* Department of Chemical and Biological Engineering, South Dakota School of Mines and Technology, Rapid City, SD, Feb 23, 2016.
243. *“Designing Functional Materials using Layer by Layer Growth,”* Department of Chemical Engineering at the University of Florida, Gainesville, FL, March 7, 2016.
244. *“Atomic Layer Deposited Transition Metal Oxides as Active Electrocatalysts for the Oxygen Evolution Reaction,”* Symposium on “Surface chemistry and catalysis of transition metal oxides,” 251st ACS National Meeting & Exposition, San Diego, CA, March 13-17, 2016.
245. *“Strategies for Selective Deposition of Metal Oxides,”* Symposium EP11, “Novel Materials for End-of-Roadmap Devices in Logic, Power and Memory”, 2016 MRS Spring Meeting, Phoenix, AZ, March 28 – Apr 1, 2016.
246. *“Understanding Nucleation and Growth of Metal Oxides by Atomic Layer Deposition,”* Symposium EP5, “Metal Oxide Hetero-Interfaces in Hybrid Electronic Platforms”, 2016 MRS Spring Meeting, Phoenix, AZ, March 28 – Apr 1, 2016.
247. *“Layer-by-Layer Synthesis of Nanoscale Materials for Energy Conversion,”* 2016 Reilly Lectures, Department of Chemical and Biomolecular Engineering, University of Notre Dame, South Bend, IN, April 5, 2016.
248. *“Powering the Future with Sustainable Energy: How Do We Get There?”* 2016 Reilly Lectures, Department of Chemical and Biomolecular Engineering, University of Notre Dame, South Bend, IN, April 6, 2016.
249. *“Creating Active Electrocatalysts for the Oxygen Evolution Reaction by Atomic Layer Deposition,”* 2016 International Conference on Metallurgical Coatings and Thin Films (ICMCTF) Symposium; Session on “Thin Films and Coatings for Photo-Electrochemical Cells”; San Diego, CA, April 25-29, 2016.
250. *“Designing Catalysts using Layer by Layer Growth,”* 2016 Summer School/Workshop: “Reactivity of nanoparticles for efficient and sustainable energy production -IV”, Kysthusene, Gilleleje, Denmark, August 7-12, 2016.
251. *“Layer-by-Layer Synthesis of Nanomaterials for Energy Applications,”* Kavli Nanoscience Symposium, Trondheim, Norway, September 7-8, 2016.
252. *“Designing Catalysts using Atomic Layer Deposition,”* Dept. of Materials Science and Engineering, NTNU, Trondheim, Norway, September 9, 2016.
253. *“Creating Catalysts using Layer by Layer Growth,”* Energy@Stanford & SLAC Summer Conference, Stanford, CA, Sept 15, 2016.
254. *“Strategies for Area Selective Deposition,”* SRC e-Workshop, October 5, 2016.
255. *“Nucleation in Atomic Layer Deposition: From Fundamentals to Applications,”* US Army Research Laboratory, Adelphi, MD, October 27, 2016.
256. *“Nucleation in Atomic Layer Deposition: From Fundamentals to Applications,”* Academic Lecture Series, Dow Chemical Company Electronic Materials Division, Marlborough, MA, October 28, 2016.
257. *“Research and Innovation in Advanced Materials for Sustainable Energy,”* International Symposium on the development of green chemistry in the world for Taiwan Industry, Industrial Development Bureau of the Ministry of Economic Affairs, Republic of China (Taiwan), November 11, 2016.
258. *“Organic Functionalization of Semiconductor Surfaces,”* Collaborative Research Center on “Hybrid Inorganic/Organic Systems for Opto-Electronics (HIOS)”, Berlin, Germany, December 15, 2016.

259. *“Understanding Surface Chemistry of Atomic Layer Deposition: Toward Renewable Energy Applications,”* Physics and Chemistry of Surfaces and Interfaces (PCSI) Conference, Santa Fe, New Mexico, Jan 15-19, 2017.
260. *“Molecular Surface Science: Uncovering Reaction Mechanisms in Electronics and Catalysis,”* 1st Morino Lecture, Institute for Solid State Physics (ISSP), University of Tokyo, Kashiwa Campus, Kashiwa, Japan, March 13, 2017.
261. *“Molecular Surface Science: Uncovering Reaction Mechanisms in Electronics and Catalysis,”* 2nd Morino Lecture, Institute for Molecular Science, Okazaki, Japan, March 14, 2017.
262. *“Molecular Surface Science: Uncovering Reaction Mechanisms in Electronics and Catalysis,”* 3rd Morino Lecture, Department of Chemistry, Kyoto University, Kyoto, Japan, March 16, 2017.
263. *“Nanoscale Materials for Energy Conversion Applications,”* Physical Society of Japan (PSJ) Spring Meeting, Osaka University, Osaka, Japan, March 17, 2017.
264. *“New Strategies for Selective Deposition of Nanoscale Materials,”* Symposium on Deposition and Etching of Nanostructures, COLL Division, Spring 2017 ACS meeting, San Francisco, CA, April 2-6, 2017.
265. *“Modifying Catalysts using Atomic Layer Deposition,”* Symposium in honor of Cynthia Friend, ACS Catalysis Division, Spring 2017 ACS meeting, San Francisco, CA, April 2-6, 2017.
266. *“New Strategies for Area Selective Atomic Layer Deposition,”* NNCI ALD Symposium, Stanford University, Stanford, CA, April 7, 2017.
267. *“New Strategies for Selective Deposition of Nanoscale Materials,”* Friday Science Colloquium, IBM – Almaden Research Center, Almaden, CA, April 14, 2017.
268. *“New Strategies for Area Selective Deposition,”* 2nd Area Selective Deposition Workshop (ASD 2017), Eindhoven, The Netherlands, April 21, 2017.
269. *“Designing Catalysts using Atomic Layer Deposition,”* Department of Chemical Engineering, Columbia University, New York, NY, April 25, 2017.
270. *“Designing Catalysts using Atomic Layer Deposition,”* Department of Chemistry, Brookhaven National Laboratory, Brookhaven, NY, April 26, 2017.
271. *“Designing Catalysts using Atomic Layer Deposition,”* Department of Chemistry, Northwestern University, Evanston, IL, April 28, 2017.
272. *“Topographical and Area Selectivity in Atomic Layer Deposition,”* EuroCVD – BalticALD Conference, Linköping, Sweden, June 11-14, 2017.
273. *“Current Approaches to Area Selective ALD,”* Symposium on Atomic Layer Deposition, Applied Materials, Santa Clara, CA, July 14, 2017.
274. *“Integrating Atomic Layer Deposition and Etching to Achieve Selective Growth,”* 4rd International Atomic Layer Etching Workshop (ALE2017), Denver, July 15-17, 2017.
275. *“Small Solutions to Big Problems: Materials at the Nanoscale,”* Summer International Honors Program, Stanford University, Stanford, CA, July 19, 2017.
276. *“Novel Molybdenum Sulfide Hybrid Films,”* Symposium on Chalcogenide Semiconductor Research and Applications (CSRA), International Materials Research Congress (IMRC) 2017 Meeting, Cancun, Mexico, Aug 21-22, 2017.
277. *“Modifying Catalysts using Atomic Layer Deposition,”* Pacific Coast Catalysis Society Annual Meeting, UC Davis, Davis, CA, Sept 18, 2017.
278. *“Selective Atomic Layer Processing,”* Strategic Materials Conference (SMC) 2017, San Jose, CA, Sept 19, 2017.
279. *“Small Solutions to Big Problems: Materials at the Nanoscale,”* New York Academy of Sciences Junior Academy, October 4, 2017.
280. *“Defect Removal Process for Area Selective ALD,”* SRC e-Workshop, October 10, 2017.
281. *“Designing Catalysts using Atomic Layer Deposition,”* Department of Chemistry, Materials Chemistry Seminar Series, Indiana University, Bloomington, IN, Oct 17, 2017.

282. “*Synthesizing Novel Catalysts Using Atomic Layer Deposition*,” Department of Chemical and Biomolecular Engineering, Georgia Institute of Technology, Atlanta, GA, Oct 25, 2017.
283. “*New Materials by Atomic and Molecular Layer Deposition*,” International Symposium on Hybrid Materials and Processing, Busan, Korea, November 5-8, 2017, Plenary Talk.
284. “*Synthesizing Novel Catalysts Using Atomic Layer Deposition*,” Department of Chemical Engineering, University of California at Santa Barbara, Santa Barbara, CA, Nov 21, 2017.
285. “*Energy Conversion Materials by Atomic and Molecular Layer Deposition*,” Department of Chemical Engineering, University of Washington, Seattle, WA, Jan 29, 2018.
286. “*Energy Conversion Materials by Atomic and Molecular Layer Deposition*,” NREL/Colorado School of Mines Distinguished Lecture Series, Golden, CO, Jan 30-31, 2018.
287. “*Molecular Functionalization of Surfaces: An Evolution from Fundamentals to Applications*,” 255th ACS National Meeting, New Orleans, LA, Mar 18-22, 2018.
288. “*Atomic Layer Deposition: From Understanding Nucleation to Area Selective Processing*,” Brewer Science, Rolla, MO, April 10, 2018.
289. “*Skimming the Surface for Energy Solutions*,” Stanford Research Conference 2018, Stanford, CA, April 13, 2018.
290. “*Skimming the Surface for Energy Solutions*,” Stanford School of Engineering Faculty Talks, Stanford, CA, May 3, 2018.
291. “*Mechanisms and Selectivity in Atomic Layer Deposition*,” Symposium on Vapor-Surface Chemistry: Mechanisms and Applications, 101st Canadian Chemistry Conference, Edmonton, Canada, May 27-31, 2018.
292. “*Area and Topographical Selectivity in Atomic Layer Deposition*,” Selective Deposition Workshop, IEEE International Interconnect Technology Conference (IITC), San Jose, CA, June 4-8, 2018.
293. “*Molecular Layer Deposition of Polymeric and Hybrid Thin Films*,” Spring Meeting of the European Materials Research Society, Strasbourg, France, June 18-22, 2018.
294. “*Area Selective Atomic Layer Deposition*,” Deep Valley Labs, San Jose, CA, June 26, 2018.
295. “*Surface Functionalization through Atomic and Molecular Layer Deposition*,” Telluride Workshop on Semiconductor Surface Chemistry, Telluride, CO, July 30-Aug 3, 2018.
296. “*Reactive Oxygen Species in Films Grown with Ozone by Atomic Layer Deposition*,” Telluride Workshop on Semiconductor Surface Chemistry, Telluride, CO, July 30-Aug 3, 2018.
297. “*Synthesizing Novel Catalysts Using Atomic Layer Deposition*,” Keynote Lecture, 6th International Workshop on Nanotechnology, Renewable Energy and Sustainability, Xian, China. Sep 17, 2018.
298. “*Applying Atomic and Molecular Layer Deposition to Catalyst Design*,” Plenary Lecture, The 4th International Conference on ALD Applications and 2018 China ALD Conference, Shenzhen, China, Oct 15-17, 2018.
299. “*Functionalizing Semiconductor Surfaces and Interfaces*,” 65th Annual AVS International Symposium, Long Beach, CA, Oct 21-26, 2018.
300. “*New Materials by Atomic and Molecular Layer Deposition*,” Stanford/ZJU Symposium, Stanford, CA, November 2, 2018.
301. “*Nanoscale Materials by Atomic and Molecular Deposition*,” Seminar at Centre for Nano and Soft Matter Sciences, Bangalore, India, Dec 19, 2018.
302. “*Using Molecular Monolayers to Achieve Selective Atomic Layer Deposition*,” Area Selective Atomic Layer Deposition session, Advanced Patterning Materials and Processes XXXVI Conference of the SPIE Advanced Lithography Symposium 2019, San Jose, CA, Feb 24-28, 2019.

303. *“Fundamentals of Atomic Layer Deposition,”* Surface Science Division, German Physics Society (DPG) Spring Meeting, Regensburg, Germany, March 31 – April 4, 2019.
304. *“Skimming the Surface for Energy Solutions,”* Joint Chemistry Seminar Series, Claremont Colleges, April 9, 2019.
305. *“Approaches to Area Selective Deposition for Next Generation Interconnects,”* 2019 Spring MRS Meeting, Symposium on Next-Generation Interconnects—Materials, Processes and Integration, Phoenix, AZ, Apr 22-26, 2019.
306. *“Area Selective Atomic Layer Deposition as an Emerging Process for Advanced Nanofabrication,”* Symposium on Silicon Compatible Emerging Materials, Processes, and Technologies for Advanced CMOS and Post-CMOS Applications 9, 235th ECS Meeting, Dallas, TX, May 26-31, 2019.
307. *“Area Selective Atomic Layer Deposition for Advanced Nanofabrication,”* Lam CTO Seminar Series, Lam Research, Fremont, CA, July 11, 2019.
308. *“Tutorial on Area-Selective ALD for Microelectronics Applications,”* 19th AVS ALD conference, Bellevue, WA, July 21-24, 2019.
309. *“Advances in Area Selective Atomic Layer Deposition,”* TSMC Corporate Research Seminar Series, August 20, 2019.
310. *“Area Selective Atomic Layer Deposition for Advanced Nanofabrication,”* Symposium on Polymer Science & Engineering in Microelectronics, ACS Fall 2019 National Meeting, San Diego, CA, August 25-29, 2019.
311. *“Mission Critical: Driving Innovation and Training the Next Generation with University Research,”* 2019 NSF STC Directors Meeting on The Research Mission of US Universities in the 21st Century, University of Southern California, Los Angeles, CA, August 28, 2019.
312. *“Area Selective Atomic Layer Deposition for Advanced Patterning,”* 2019 Lithography Workshop, Palm Spring, CA, November 3-7, 2019.
313. *“Organic-inorganic hybrids at the interface and in ultrathin films,”* 2nd funCOS International Workshop, Erlangen, Germany, Nov 17-19, 2019.
314. *“Area selective deposition,”* Veeco Instruments’ Technical Advisory Board (TAB) Meeting, San Jose, CA, February 29, 2020.
315. *“Process Innovations for Semiconductor Technology using Area Selective Atomic Layer Deposition,”* Keynote Lecture, Thin Film and Integration Symposium IV, China Semiconductor Technology International Conference (CSTIC) 2020, Shanghai, China (March 15-16, 2020—cancelled).
316. *“Semiconductor surface functionalization: From self-assembly to photoinitiated film growth,”* Symposium on Semiconductor Surfaces: From Chemistry and Function to Applications, COLL Division, ACS Spring 2020 National Meeting, Philadelphia, PA, March 22-26, 2020—virtual symposium, live session talk.
317. *“Using atomic-scale surface modification to understand support and promoter effects of syngas conversion catalysts,”* Symposium on Activation of Light (C1-C4) Hydrocarbons. Theory and Experiments, CATL Division, ACS Spring 2020 National Meeting, Philadelphia, PA (March 22-26, 2020—to be rescheduled).
318. *“From Computer Chips to Catalysts: Precise Materials Synthesis for Sustainable Energy Applications,”* Student invited colloquium, Department of Chemical and Biomolecular Engineering, UC Berkeley, Berkeley, CA, Virtual seminar, September 30, 2020.
319. *“Thin film growth one step at a time: unraveling mechanisms in atomic layer deposition,”* AVS 67 Virtual Showcase, Live session talk, October 27, 2020.
320. *“Understanding Area Selective Atomic Layer Deposition by a Comparative Study of Precursors,”* Symposium on ‘Surfaces and Interfaces in Electronics and Photonics’, Spring-Fall Virtual 2020 MRS Meeting, Live session and On-demand talk, Nov 27-Dec 4, 2020.

321. *“Atomic Layer Deposition of Electron and Hole Transport Layers for Perovskite Solar Cells,”* Symposium on “Contacting Materials and Interfaces for Optoelectronic Devices,” Spring-Fall Virtual 2020 MRS Meeting, On-demand talk, Nov 27-Dec 4, 2020.
322. *“From Computer Chips to Catalysts: Precise Materials Synthesis for Sustainable Energy Applications,”* Racheff Award Lecture, University of Illinois, Department of Materials Science and Engineering, Urbana-Champaign, IL, virtual, April 12, 2021.
323. *“A surface scientist’s take on atomic layer deposition,”* Interdisciplinary Surface Science Conference (ISSC-23), virtual, April 19-21, 2021, Plenary Talk (live).
324. *“Area Selective Atomic Layer Deposition for Advanced Microelectronics,”* 2021 Workshop of Microelectronics and Electron Devices, WMED2021, virtual (live), April 23, 2021.
325. *“From Computer Chips to Catalysts: Precise Materials Synthesis for Sustainable Energy Applications,”* Dorn Lecture, Department of Materials Science and Engineering, Northwestern University, Evanston, IL, virtual (live), May 4, 2021.
326. *“Thin film growth one step at a time: understanding atomic layer deposition,”* India ALD online conference (June 15, 2021, to be rescheduled).
327. *“Mechanisms of ALD: Toward Applications in Area Selective Deposition,”* Symposium G01 on Atomic Layer Deposition Applications, 17, 240th ECS Fall Meeting, virtual (live), October 10-14, 2021, Keynote Talk.
328. *“Mechanisms of Film Growth by Atomic Layer Deposition,”* in Surface chemistry of film growth and etching, 67th International AVS Symposium, virtual (rescheduled from 66th symposium), October 24-29, 2021, on demand.
329. *“Selectivity in Atomic Layer Deposition,”* Keynote Speech, 5th International Conference on ALD Applications & 1st Asian ALD Conference (2020 China ALD), Wuhan, China, (rescheduled to November 7-10, 2021).
330. *“Precise Materials Synthesis One Layer at a Time,”* Annual AIChE Meeting, MESD Plenary Session, Boston, MA, November 7-12, 2021, Plenary Talk.
331. *“Understanding and Tuning Surface Chemistry to Achieve Area Selective ALD,”* Symposium on Advanced atomic layer deposition and chemical vapor deposition techniques and applications, MRS Fall Meeting, Boston, MA, virtual, Nov. 28 – Dec. 3, 2021.
332. *“Functional Assemblies at Surfaces using Molecular Layer Deposition,”* Symposium on Supramolecular Assembly at Surfaces: Nanopatterning, Functionality, Reactivity, Pacificchem 2021, rescheduled from Honolulu, HI to virtual, December 16 – 21, 2021.
333. *“Nanomaterials for Energy Applications,”* Azeotropy IIT Bombay Conference, virtual, February 4, 2022.
334. *“Area Selective Atomic Layer Deposition for Advanced Patterning,”* Meta Reality Labs, virtual, February 18, 2022.
335. *“Progress in Area Selective Deposition,”* SRC e-Workshop, virtual, March 15, 2022.
336. *“Tuning Catalyst Performance Using Precise Materials Synthesis,”* Department of Chemical and Environmental Engineering, Yale University, New Haven, CT, virtual, April 6, 2022.
337. *“Using Chemical Selectivity to Control Atomic Placement in ALD,”* ASD2022 workshop, San Francisco, CA, April 21-22, 2022, Keynote Talk.
338. *“Guiding Area Selective Deposition by a Mechanistic Understanding of Surface Chemistry,”* Symposium on Surfaces and Interfaces in Electronics and Photonics, 2022 MRS Spring Meeting, in Honolulu, HI, May 08-May 13, 2022.
339. *“ALD Mechanisms,”* Department of Physics, Lund University, Lund, Sweden, May 19, 2022.
340. *“Functional Thin Films by Molecular Layer Deposition,”* symposium on “Polymer and Hybrid Thin Films Deposited from the Vapor Phase for Functional (Bio-)Devices”,

- European Materials Research Society (E-MRS) meeting, Strasburg, France, virtual, May 30- June 3, 2022.
341. *"From Mechanisms to Selectivity in Atomic Layer Deposition,"* Yanagida Research Group seminar, Department of Applied Chemistry, School of Engineering, University of Tokyo, virtual, June 14, 2022.
342. *"Up, Down and All Around: Controlling Atomic Placement in ALD,"* ALD/ALE 2022, Ghent, Belgium, June 26-29, 2022, Plenary Award Talk.
343. *"Surface Reaction Mechanisms in Atomic Layer Deposition,"* Telluride Science Research Center (TSRC) Workshop on Semiconductor Surface Chemistry, Telluride, CO, July 25-29, 2022.
344. *"Using atomic-scale surface modification to understand support and promoter effects of syngas conversion catalysts,"* Symposium on Surface Chemistry and Spectroscopy: A Symposium Inspired by the Research Contributions of Peter Stair, 264th National ACS Meeting, Chicago, IL, Aug 21-25, 2022.
345. *"Use of Self-Assembled Monolayers to Achieve Area Selective Deposition,"* Symposium on "Advanced Materials by Self-Assembly: Fabrication and Applications," 2nd International Conference on Materials for Humanity (MH 22), Materials Research Society of Singapore (MRS-S), Singapore, hybrid/virtual, Sept 19-21, 2022.
346. *"Applying atomic-scale surface modification to enhance syngas conversion catalysis,"* 2022 DOE BES Catalysis Science Program, virtual, Sept 26-28, 2022.
347. *"Future Semiconductor Materials and Processes,"* SRC-SIA Webinar on Collaboration Towards Decadal Plan Goals: Emerging Semiconductor Technologies, virtual, Sept 29, 2022, plenary.
348. *"Engineering Interfaces for Electrochemical Devices using Atomic Layer Deposition,"* 14th Solid State Ionic Devices symposium in honor of Fritz Prinz, Electrochemical Society (ECS) Meeting, Atlanta, GA, keynote, October 9-13, 2022.
349. *"Harnessing chemical selectivity for advanced materials deposition,"* California Research Alliance "CARA" Meeting, BASF, UC Santa Barbara, CA, keynote, November 3, 2022.
350. *"Controlling Atomic Layer Deposition for Advanced Semiconductor Manufacturing,"* 1st Korea International Semiconductor Conference on Manufacturing Technology (KISM), Busan, Korea, November 13-16, 2022, plenary.
351. *"Area Selective Atomic Layer Deposition for Advanced Device Processing,"* 43rd International Symposium on Dry Process (DPS 2022), Osaka, Japan, November 24-25, 2022, hybrid/virtual.
352. *"Opportunities for Advanced Patterning by Selective Deposition,"* Korean Conference on Semiconductors, Hi One Resort, Korea, plenary, Feb 13-15, 2023.
353. *"DEIB efforts: A US perspective,"* Korean Conference on Semiconductors, Hi One Resort, Korea, Feb 13-15, 2023.
354. *"From Mechanisms to Selectivity in Atomic Layer Deposition,"* Seminar, SK Hynix, Seoul, South Korea, February 16, 2023.
355. *"From Mechanisms to Selectivity in Atomic Layer Deposition,"* Seminar, Samsung Advanced Institute of Technology (SAIT), Seoul, South Korea, February 17, 2023.
356. *"Progress in Area Selective Deposition,"* Seminar, Samsung Electronics, Seoul, South Korea, February 17, 2023.
357. *"Engineering Interfaces for Energy Storage and Catalysis using Atomic Layer Deposition,"* Department of Chemical and Biomolecular Engineering, Cornell University, Ithaca, NY, May 1, 2023.
358. *"Precise Materials Synthesis One Layer at a Time: Toward Catalysis and Energy Storage,"* Department of Energy Science and Engineering, Stanford University, Stanford, CA, (May 8, 2023.—postponed due to COVID).

359. *“High-Throughput and Atomically Efficient Synthesis for Nano/Microelectronics,”* SLAC Workshop on the Future of Nano/Microelectronics, Menlo Park, CA, Keynote, May 26, 2023.
360. *“Applying atomic-scale surface modification to catalysis and energy storage,”* Symposium in Honor of the 2021 R.H. Wilhelm Award Winner, AIChE Annual Meeting, Orlando, FL, November 5-10, 2023, keynote.
361. *“Controlling nucleation and selectivity in atomic layer deposition,”* Symposium on Material Interfaces as Energy Solutions in honor of John Ekerdt, AIChE Annual Meeting, Orlando, FL, November 5-10, 2023.
362. *“Nanoscale Materials Synthesis for Sustainable Energy Applications,”* VII National Congress of Nanotechnology, Pucón, Chile, November 12-15, 2023, keynote.
363. *“Panel on Women in STEM: The role of female mentorship,”* VII National Congress of Nanotechnology, Pucón, Chile, November 12-15, 2023.
364. *“Precision synthesis for microelectronics: understanding and controlling deposition,”* SSRL Scientific Advisory Committee meeting, Menlo Park, CA, March 12, 2024.
365. *“Panel: Impactful Publishing in ASD,”* Invited panelist, Area Selective Deposition 2024 Workshop, Montreal, Canada, April 14-17, 2024.
366. *“Controlling Interfaces Toward Area Selective Atomic Layer Deposition,”* Symposium on Surfaces and Interfaces in Electronics and Photonics, MRS Spring Meeting, Seattle, WA, April 22-26, 2024.
367. *“Precise Materials Synthesis One Layer at a Time: Toward Catalysis and Energy Storage,”* University of Washington Chemical Engineering Chair’s Distinguished Lecture, Seattle, WA, May 6, 2024.
368. *“Controlling lithium morphology by interfacial engineering,”* Keynote talk, 22nd International Meeting on Li Batteries, Hong Kong, China, June 16-21, 2024.
369. *“Applying Interfacial Engineering to Lithium Batteries,”* Distinguished Workshop on Electrochemical Energy Storage at The Hong Kong University of Science and Technology (HKUST), Hong Kong, China, June 18, 2024.
370. *“Area Selective Atomic Layer Deposition: What, What for, and What Next?”*, Invited Tutorial, ALD/ALE 2024 Conference, Helsinki, Finland, August 4-7, 2024.
371. *“Molecular Layer Deposition of Metal Coordination Polymer Resists Toward EUV Lithography,”* Symposium on Advanced patterning chemistry: materials and methods for next generation semiconductors, PMSE Division, ACS Fall Meeting, Denver, CO, August 18 - 22, 2024.
372. *“Precise Materials Synthesis One Layer at a Time: Toward Catalysis and Energy Storage,”* Department of Chemical and Biomolecular Engineering, New York University, Brooklyn, NY, September 13, 2024.
373. *“Area Selective Deposition and Infiltration: A Versatile Tool for Advanced Patterning,”* 2024 Lithography Workshop, San Diego, CA, November 4-7, 2024.
374. *“Precision materials synthesis for computing hardware,”* SSRL Virtual Workshop on Accelerating Research on Novel Approaches for Energy-Efficient Computing, Stanford, CA, Feb 6, 2025.
375. *“Atomic Layer Deposition for Future Microelectronics,”* Texas Materials Institute seminar series, University of Texas at Austin, Austin, TX, Feb 12, 2025.
376. *“Molecular design in area-selective atomic layer deposition,”* Micron Technology, Boise, ID, March 17, 2025.
377. *“Gas-Surface Chemistry in Atomic Layer Deposition,”* Wilhelm-Ostwald Institute for Physical and Theoretical Chemistry, University of Leipzig, Germany, March 27, 2025.
378. *“Controlling nucleation and selectivity in atomic layer deposition for materials synthesis,”* BASF, Ludwigshafen, Germany, March 28, 2025.

379. “*Area Selective Atomic Layer Deposition for Future Microelectronics*,” Session on Selective Atomic Processes, Society of Vacuum Coaters (SVC) 68th Technical Conference (TECHCON), Nashville, TN, May 17-22, 2025.
380. “*Nanoscale Coatings and Interfacial Engineering for Lithium Batteries*,” Symposium on Low Dimensional Battery Chemistries: Nanostructures, Coatings, and Thin Films, Fall ACS Meeting, Washington, DC, August 17-21, 2025.
381. “*Area Selective ALD for Future Engineering Challenges*,” Session on Area Selective Processing, Plasma Science and Technology Division, 71st Annual AVS International Symposium, Charlotte, NC, September 21-26, 2025.
382. “*Atomic Precision: Advancing Lithium Batteries through Interface Engineering*,” Department of Chemical Engineering, University of Rochester, Rochester, NY, October 8, 2025.
383. “*Area Selective ALD: Looking Back and Looking Forward*,” 248th Electrochemical Society Meeting, Chicago, IL, October 12-16, 2025.